



**Joint Instrumentation Seminar
of the Particle Physics and Photon Science communities
at DESY, Hamburg University and XFEL**

- 26 March 2010 -



**Development of radiation tolerant
silicon detectors for the Super - LHC**

*... with strong focus on the results
of the RD50 collaboration*

Michael Moll (CERN/PH)



Outline



- **Motivation to develop radiation harder detectors**
 - Super-LHC and expected radiation levels at the Super-LHC
 - Radiation induced degradation of detector performance

- **Radiation Damage in Silicon Detectors**
 - Macroscopic damage (changes in detector properties)
 - Microscopic damage (crystal damage)

- **Approaches to obtain radiation hard sensors**
 - **Material Engineering**
 - Silicon materials – FZ, MCZ, DOFZ, EPI
 - Other semiconductors
 - **Device Engineering**
 - p-in-n, n-in-n and n-in-p sensors
 - 3D sensors and thin devices

- **Silicon Sensors for the LHC upgrade and open questions**
 - Collected Charge – Signal to Noise – Avalanche effects
 - Mixed irradiations

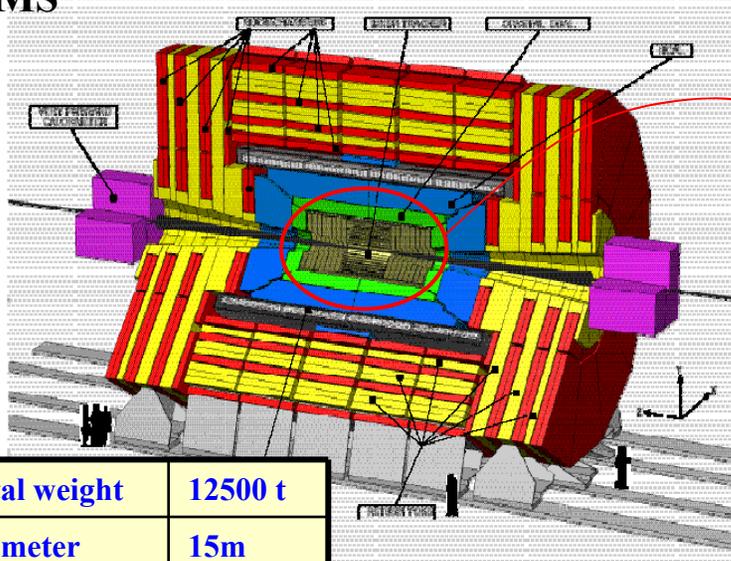
- **Summary**



LHC example: CMS inner tracker

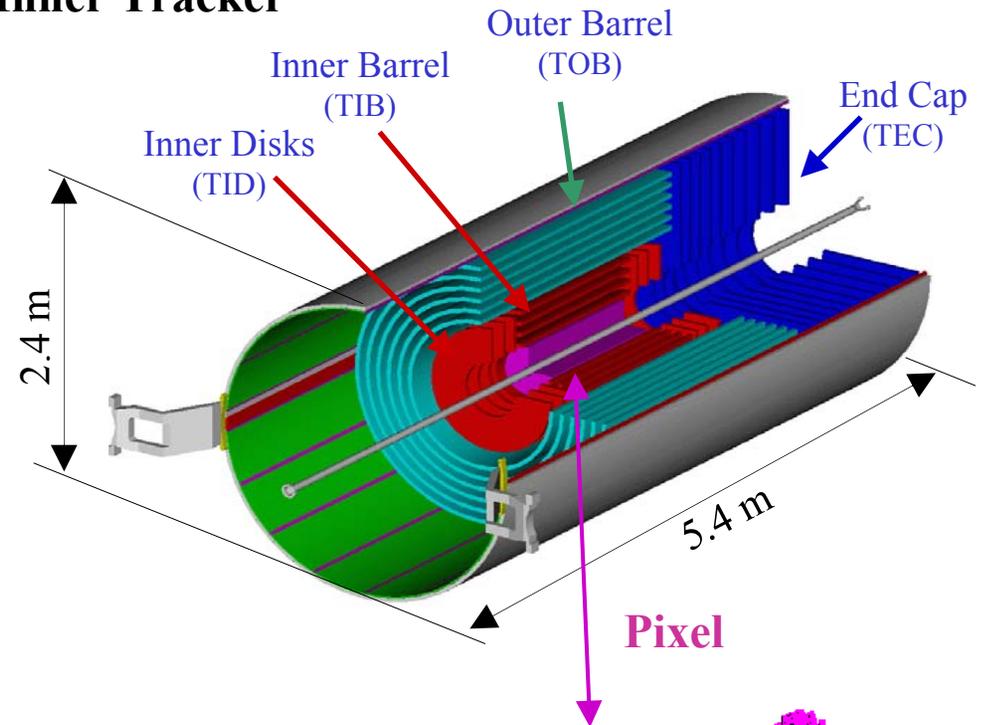


■ CMS



Total weight	12500 t
Diameter	15m
Length	21.6m
Magnetic field	4 T

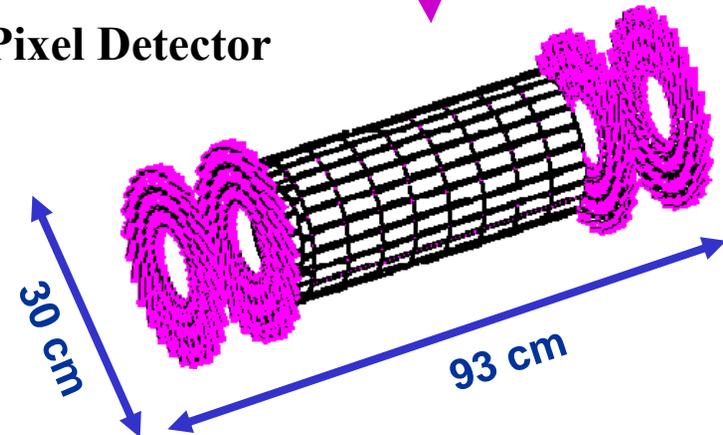
■ Inner Tracker



■ CMS – “Currently the Most Silicon”

- **Micro Strip:**
- ~ 214 m² of silicon strip sensors, 11.4 million strips
- **Pixel:**
- Inner 3 layers: silicon pixels (~ 1m²)
- 66 million pixels (100x150μm)
- Precision: $\sigma(r\phi) \sim \sigma(z) \sim 15\mu\text{m}$
- Most challenging operating environments (LHC)

■ Pixel Detector

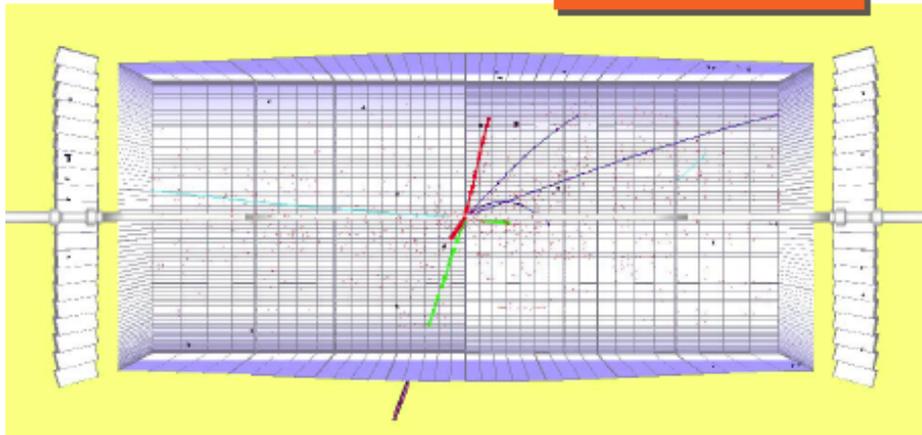




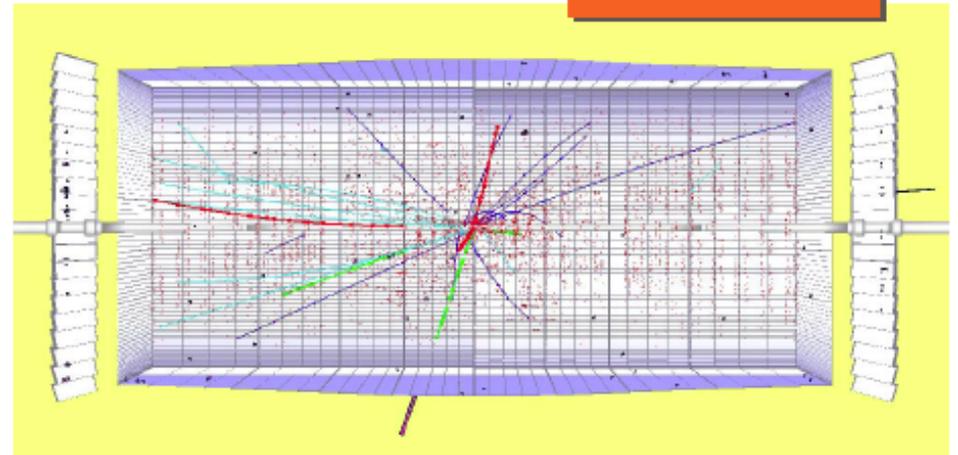
The challenge: Super LHC - visually



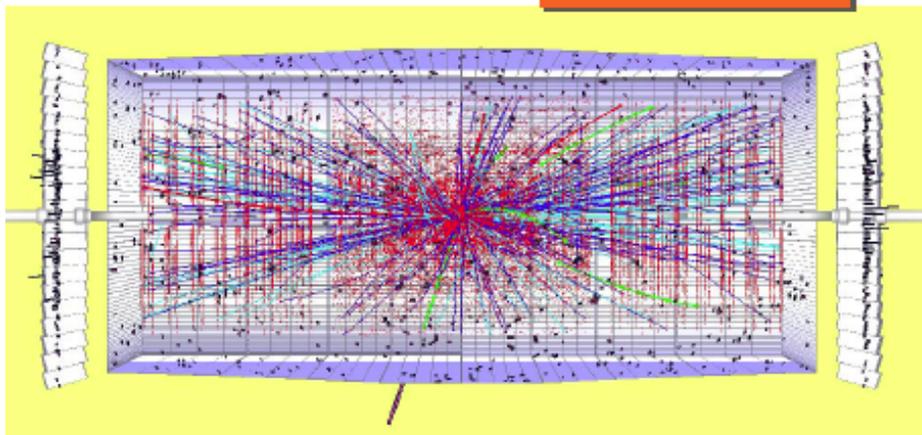
$10^{32} \text{ cm}^{-2} \text{ s}^{-1}$



$10^{33} \text{ cm}^{-2} \text{ s}^{-1}$

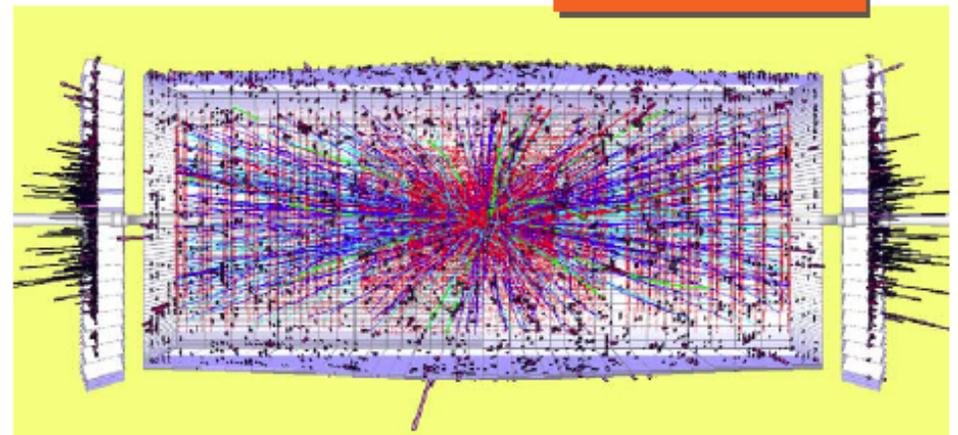


$10^{34} \text{ cm}^{-2} \text{ s}^{-1}$



?

$10^{35} \text{ cm}^{-2} \text{ s}^{-1}$

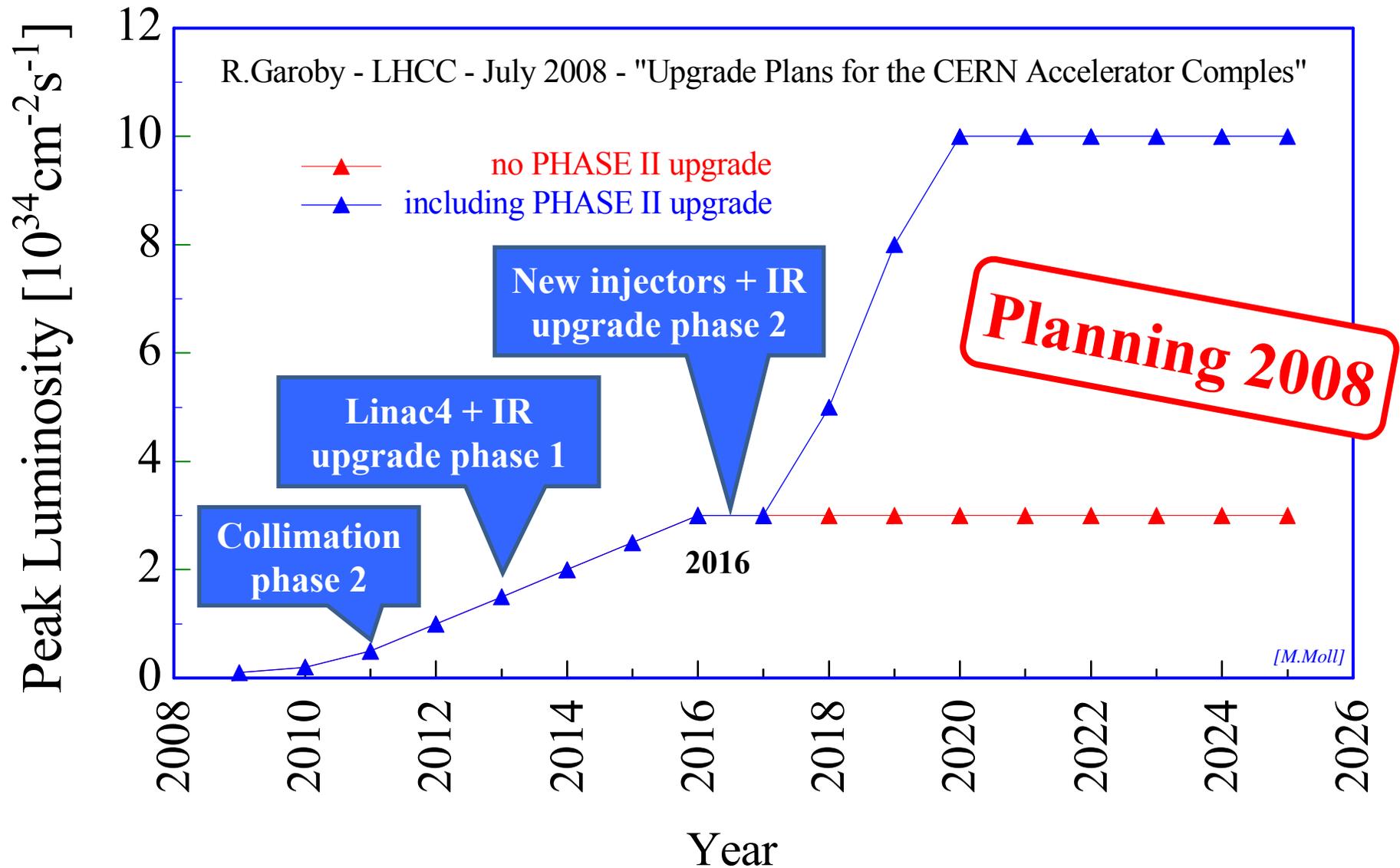


LHC nominal luminosity

SLHC luminosity ~300-400 interactions/bx

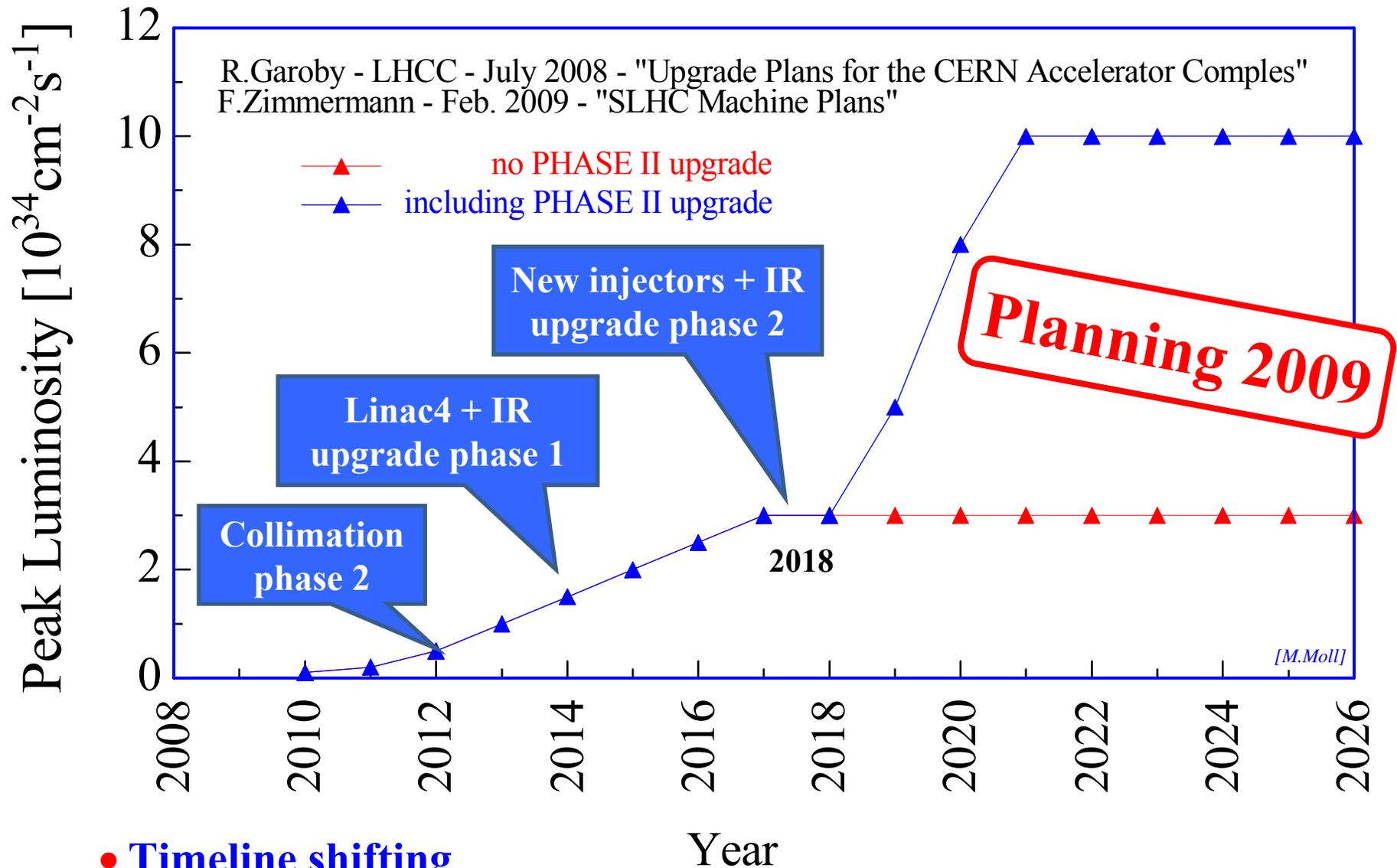


Future Plans: Towards sLHC





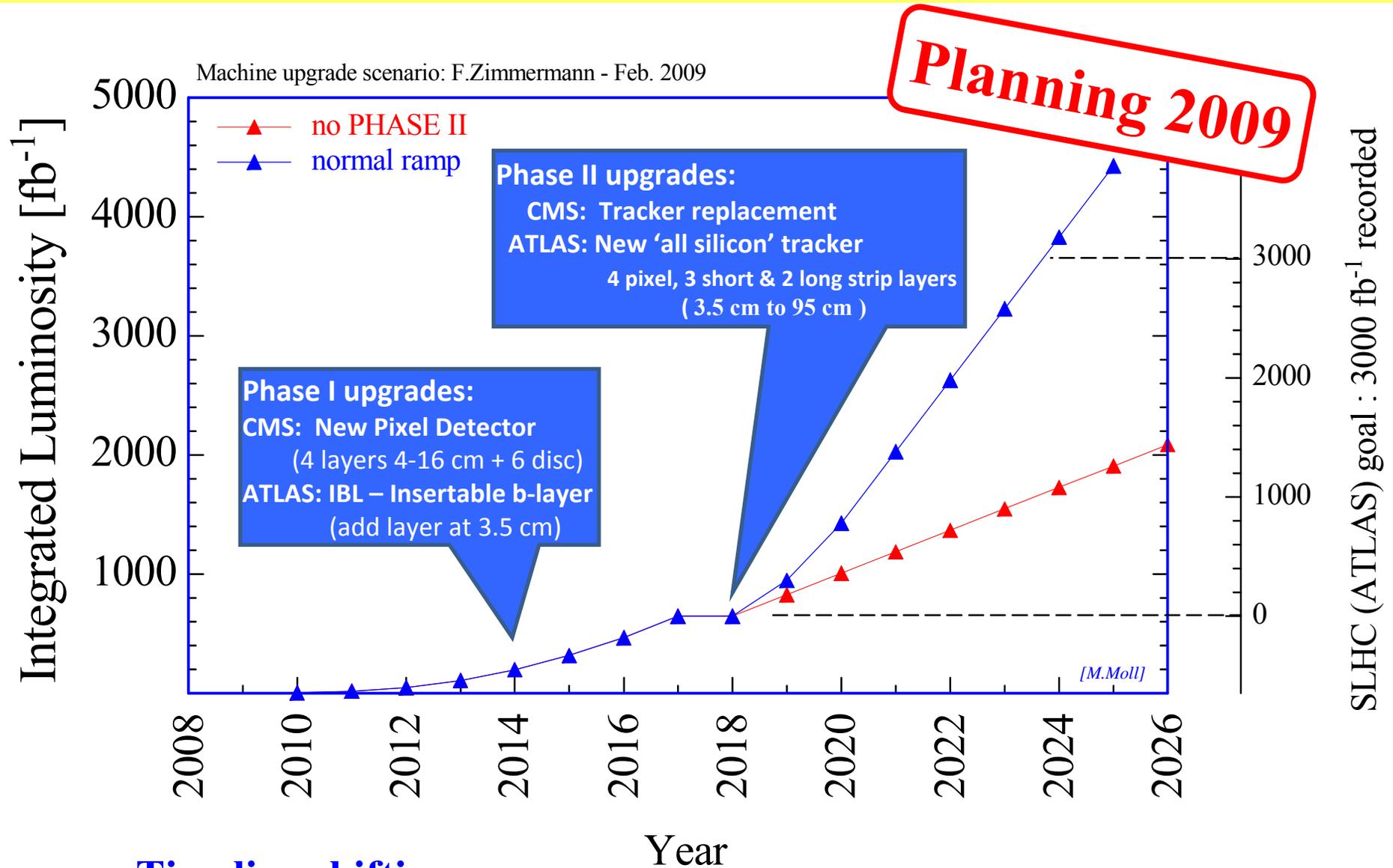
Future Plans: Towards sLHC



- **Timeline shifting**



Future Plans: Towards sLHC



- **Timeline shifting**



Future Plans: Towards sLHC



2009

Start of LHC

Ramp up luminosity to few $10^{32} \text{ cm}^{-2}\text{s}^{-1}$
Energy of 3.5 TeV per beam (50%)

- 19. March 2010 – Beams accelerated to 3.5 TeV
- 30. March 2010 – First collisions at 2 x 3.5 TeV ... run for 2 years

Planning 2010

(very uncertain at the moment)



new timeline
in
June 2010 ?

2012

Modify splices ... go to 7 TeV

Run at 7 TeV per beam and ramp up luminosity to ~30% nominal

2016

New Linac 4 injector and full collimation scheme Small upgrades to ATLAS and CMS

New Pixel

Ramp up luminosity even slightly beyond nominal

~2020

sLHC: New LHC focusing magnets, CRAB cavities, ... Major Upgrades of ATLAS and CMS

New Tracker

Collect data until **> 3000 fb⁻¹**

Use this value
for further
discussions

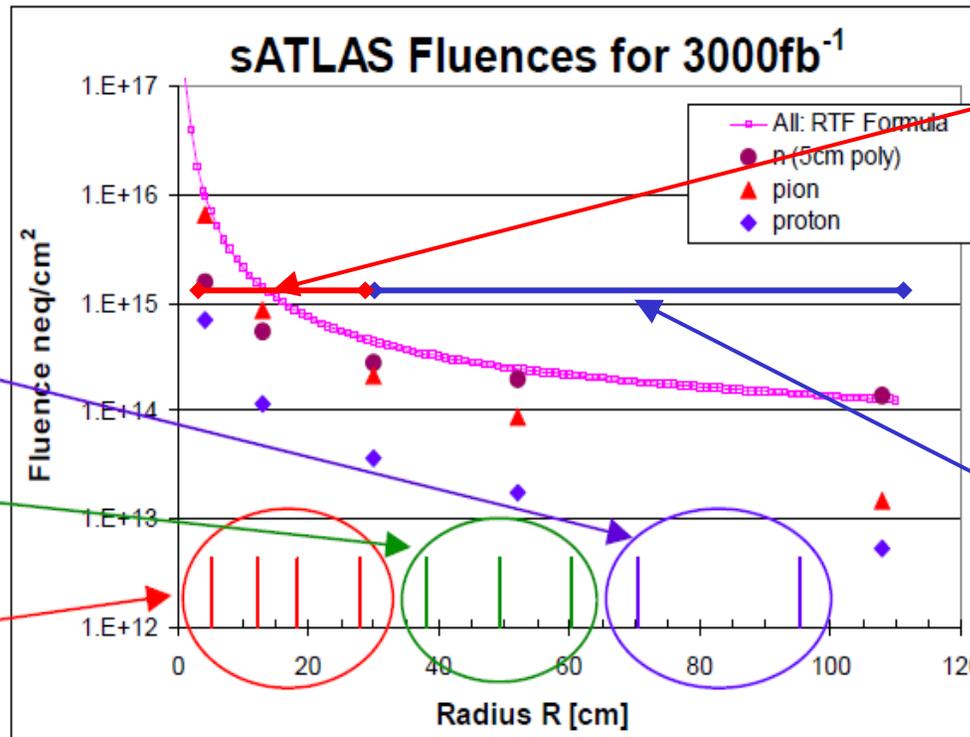


Radiation levels after 3000 fb⁻¹



Radial distribution of sensors determined by Occupancy

- Long Strips (up to $4 \times 10^{14} \text{cm}^{-2}$)
- Short Strips (up to 10^{15}cm^{-2})
- Pixels (up to 10^{16}cm^{-2})



ATLAS Radiation Taskforce [ATL-GEN-2005-01] & H.Sadrozinski [IEEE NSS 2007]

• Radiation hardness requirements (including safety factor of 2)

- $2 \times 10^{16} \text{ n}_{\text{eq}}/\text{cm}^2$ for the innermost pixel layers
- $7 \times 10^{14} \text{ n}_{\text{eq}}/\text{cm}^2$ for the innermost strip layers

B-layer (R=3.7 cm):	$2.5 \times 10^{16} \text{ n}_{\text{eq}}/\text{cm}^2 = 1140 \text{ Mrad}$
2 nd Inner Pixel Layer (R=7 cm):	$7.8 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2 = 420 \text{ Mrad}$
1 st Outer Pixel Layer (R=11 cm):	$3.6 \times 10^{15} \text{ n}_{\text{eq}}/\text{cm}^2 = 207 \text{ Mrad}$
Short strips (R=38 cm):	$6.8 \times 10^{14} \text{ n}_{\text{eq}}/\text{cm}^2 = 30 \text{ Mrad}$
Long strips (R=85 cm):	$3.2 \times 10^{14} \text{ n}_{\text{eq}}/\text{cm}^2 = 8.4 \text{ Mrad}$

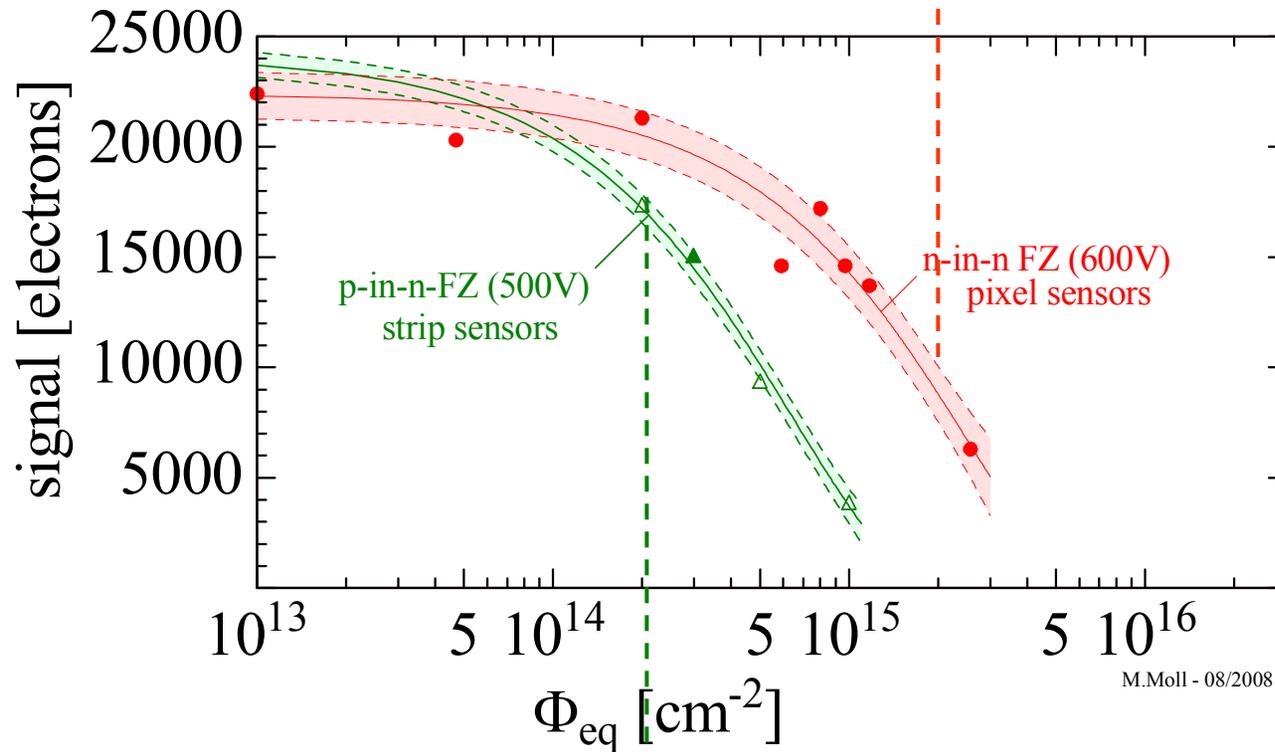


Signal degradation for LHC Silicon Sensors



Pixel sensors:
max. cumulated fluence for **LHC**

Note: Measured partly under different conditions!
Lines to guide the eye (no modeling)!



FZ Silicon
Strip and Pixel Sensors

- n-in-n (FZ), 285 μ m, 600V, 23 GeV p
- ▲ p-in-n (FZ), 300 μ m, 500V, 23GeV p
- △ p-in-n (FZ), 300 μ m, 500V, neutrons

References:

- [1] p/n-FZ, 300 μ m, (-30°C, 25ns), strip [Casse 2008]
- [2] n/n-FZ, 285 μ m, (-10°C, 40ns), pixel [Rohe et al. 2005]

Strip sensors:
max. cumulated fluence for **LHC**

Situation in 2005

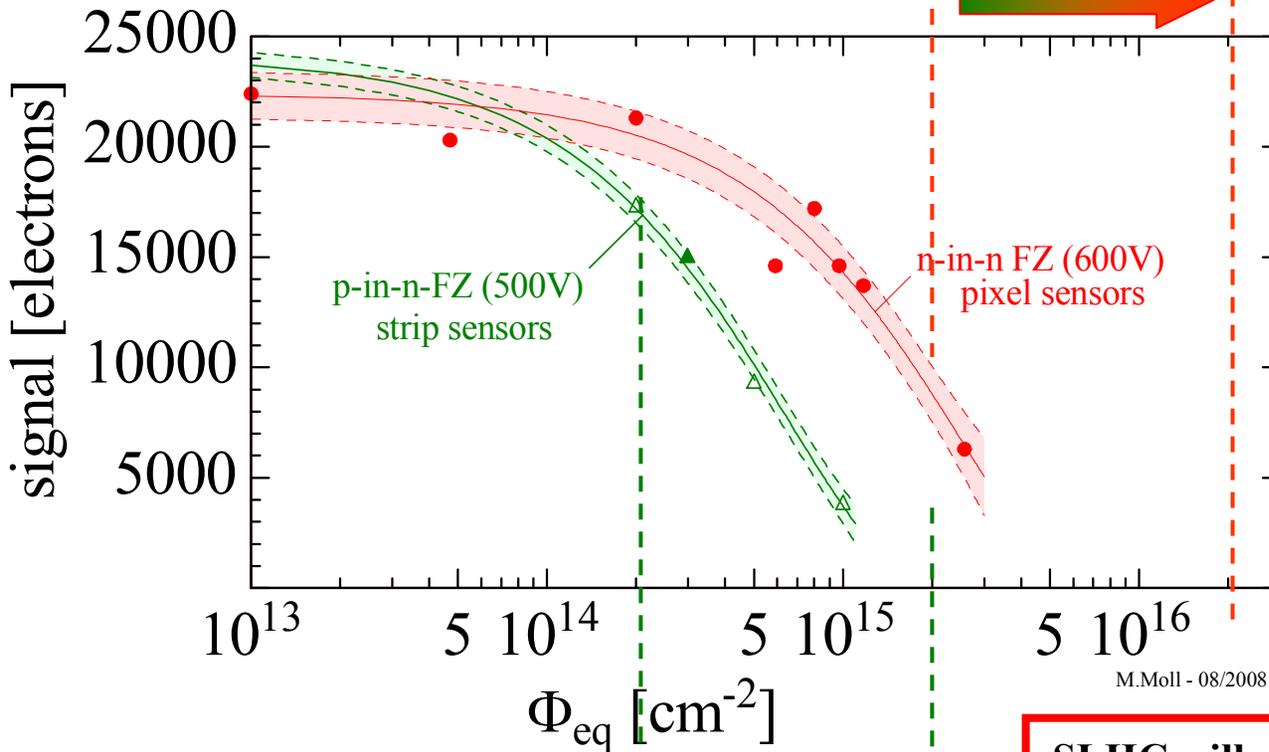


Signal degradation for LHC Silicon Sensors



Pixel sensors:

max. cumulated fluence for **LHC** and **SLHC**



Note: Measured partly under different conditions!
Lines to guide the eye (no modeling)!

FZ Silicon Strip and Pixel Sensors

- n-in-n (FZ), 285 μm , 600V, 23 GeV p
- ▲ p-in-n (FZ), 300 μm , 500V, 23GeV p
- △ p-in-n (FZ), 300 μm , 500V, neutrons

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M.Moll - 08/2008

Strip sensors:

max. cumulated fluence for **LHC** and **SLHC**

SLHC will need more radiation tolerant tracking detector concepts!

*Boundary conditions & other challenges:
Granularity, Powering, Cooling, Connectivity,
Triggering, Low mass, Low cost!*



Outline

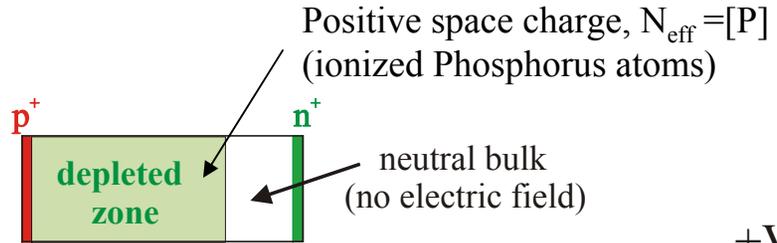


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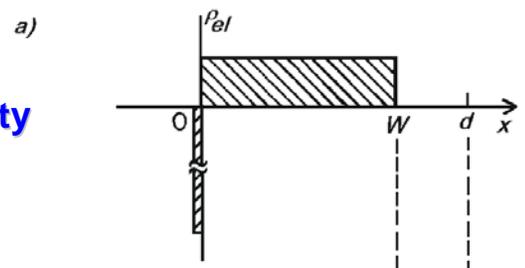
Reminder: Reverse biased abrupt p⁺-n junction

Poisson's equation

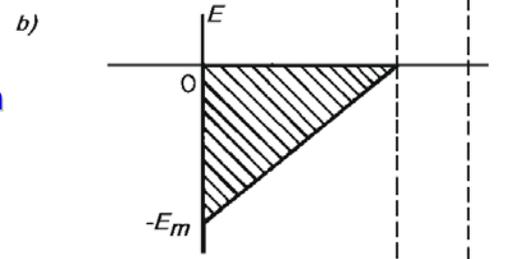
$$-\frac{d^2}{dx^2} \phi(x) = \frac{q_0}{\epsilon\epsilon_0} \cdot N_{eff}$$



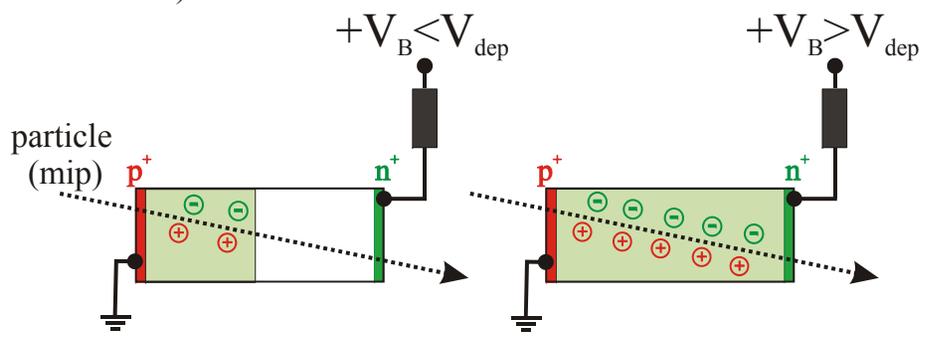
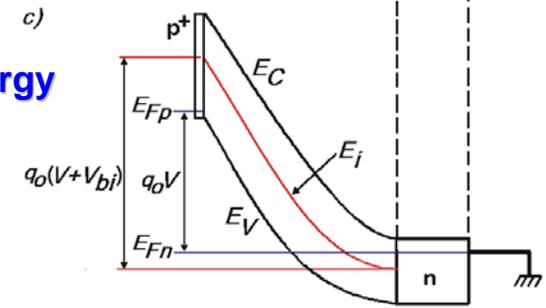
Electrical charge density



Electrical field strength



Electron potential energy



Full charge collection only for $V_B > V_{dep}$!

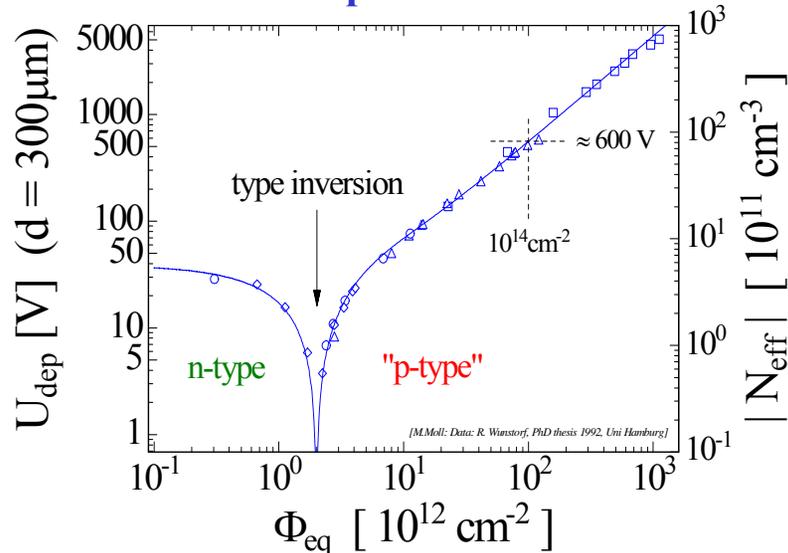
depletion voltage

$$V_{dep} = \frac{q_0}{\epsilon\epsilon_0} \cdot |N_{eff}| \cdot d^2$$

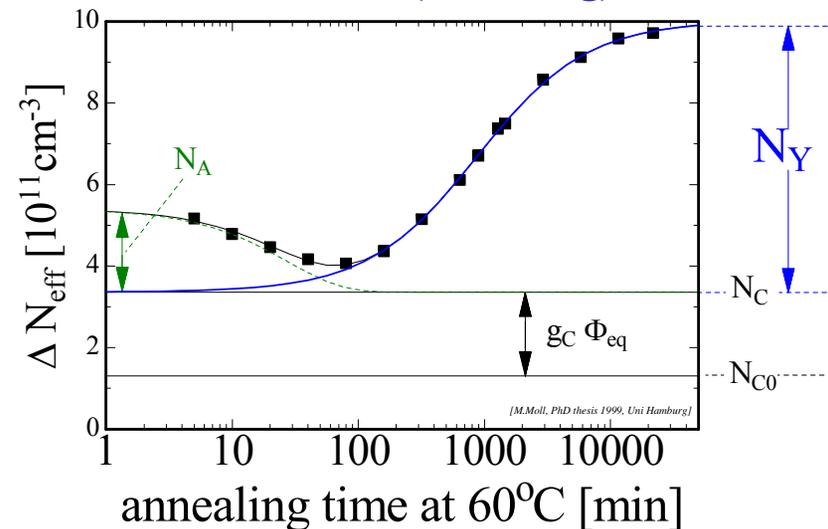
effective space charge density

Change of Depletion Voltage V_{dep} (N_{eff})

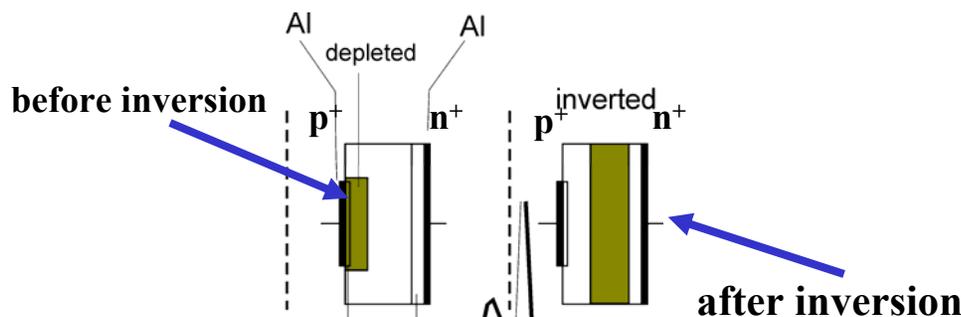
.... with particle fluence:



.... with time (annealing):



- “**Type inversion**”: N_{eff} changes from positive to negative (Space Charge Sign Inversion)



- Short term: “**Beneficial annealing**”
- Long term: “**Reverse annealing**”

- time constant depends on temperature:

~ 500 years (-10°C)

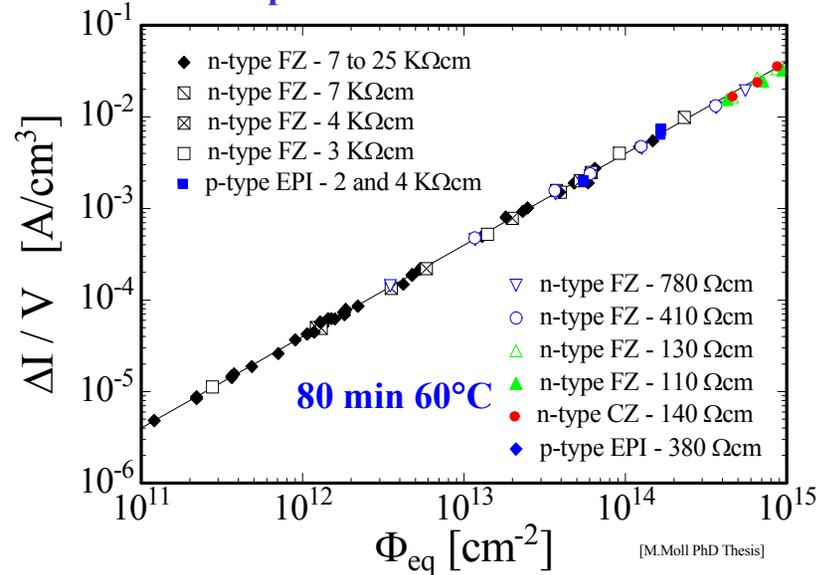
~ 500 days (20°C)

~ 21 hours (60°C)

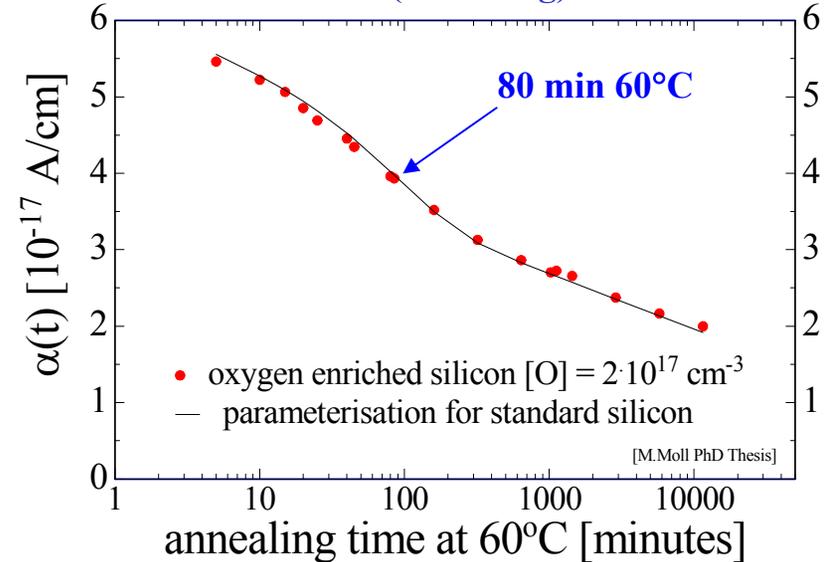
- Consequence: **Detectors must be cooled even when the experiment is not running!**

Change of Leakage Current (after hadron irradiation)

.... with particle fluence:



.... with time (annealing):



- Damage parameter α (slope in figure)

$$\alpha = \frac{\Delta I}{V \cdot \Phi_{eq}}$$

Leakage current
per unit volume
and particle fluence

- α is constant over several orders of fluence and independent of impurity concentration in Si
⇒ can be used for fluence measurement

- Leakage current decreasing in time (depending on temperature)
- Strong temperature dependence

$$I \propto \exp\left(-\frac{E_g}{2k_B T}\right)$$

Consequence:

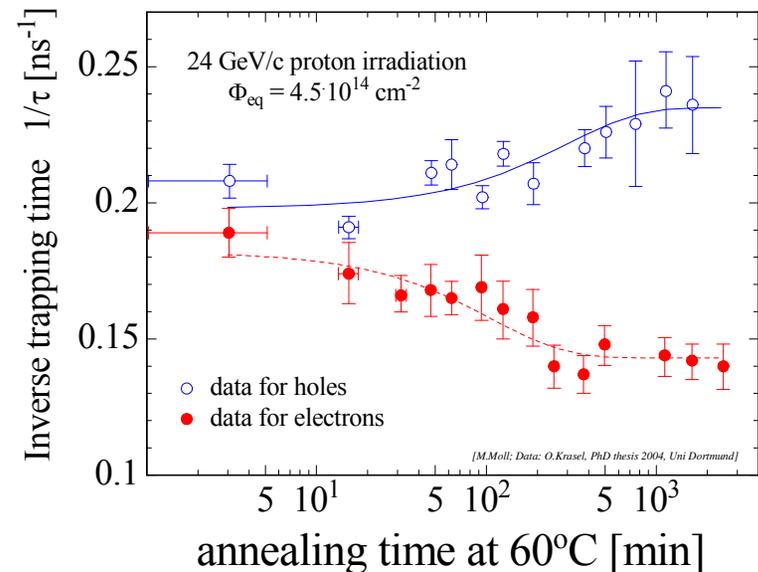
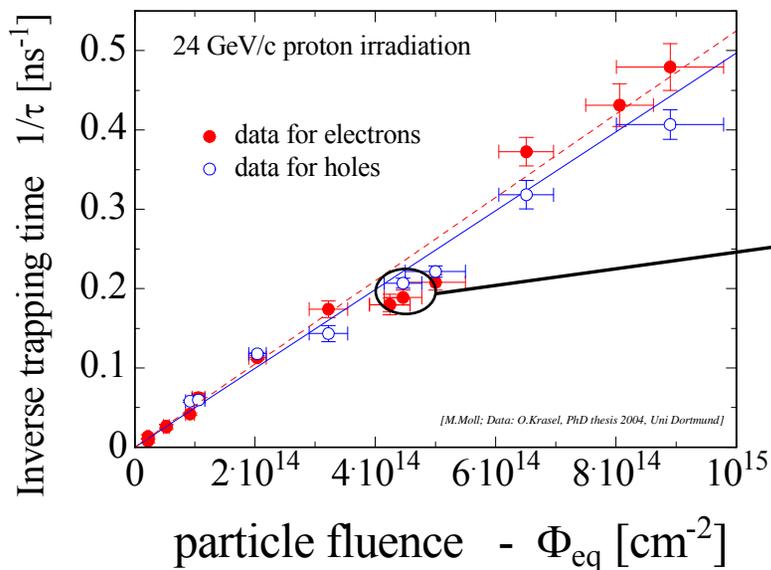
Cool detectors during operation!
Example: $I(-10^\circ\text{C}) \sim 1/16 I(20^\circ\text{C})$

■ Deterioration of Charge Collection Efficiency (CCE) by trapping

Trapping is characterized by an effective trapping time τ_{eff} for electrons and holes:

$$Q_{e,h}(t) = Q_{0,e,h} \exp\left(-\frac{1}{\tau_{\text{eff } e,h}} \cdot t\right) \quad \text{where} \quad \frac{1}{\tau_{\text{eff } e,h}} \propto N_{\text{defects}}$$

Increase of inverse trapping time ($1/\tau$) with fluence and change with time (annealing):





Summary: Radiation Damage in Silicon Sensors



■ Two general types of radiation damage to the detector materials:

● Bulk (Crystal) damage due to Non Ionizing Energy Loss (NIEL)

- displacement damage, built up of crystal defects –

Influenced
by impurities
in Si – Defect
Engineering
is possible!

I. Change of **effective doping concentration** (higher depletion voltage, under- depletion)

II. Increase of **leakage current** (increase of shot noise, thermal runaway)

III. Increase of **charge carrier trapping** (loss of charge)

Same for
all tested
Silicon

materials!

● Surface damage due to Ionizing Energy Loss (IEL)

- accumulation of positive in the oxide (SiO_2) and the Si/ SiO_2 interface –
affects: interstrip capacitance (noise factor), breakdown behavior, ...

■ Impact on detector performance and Charge Collection Efficiency (depending on detector type and geometry and readout electronics!)

Signal/noise ratio is the quantity to watch

⇒ Sensors can fail from radiation damage !

Can be
optimized!



Outline



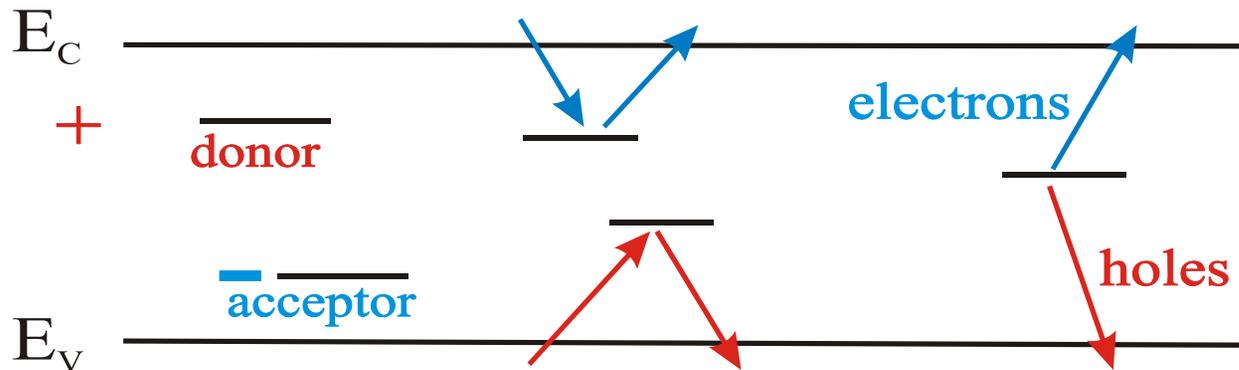
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Impact of Defects on Detector Properties



Shockley-Read-Hall statistics



charged defects
⇒ N_{eff} , V_{dep}
e.g. donors in upper
and acceptors in
lower half of band
gap

Trapping (e and h)
⇒ **CCE**
shallow defects do not
contribute at room
temperature due to fast
detrapping

generation
⇒ **leakage current**
Levels close to
midgap
most effective

Impact on detector properties can be calculated if all defect parameters are known:

$\sigma_{n,p}$: cross sections

ΔE : ionization energy

N_t : concentration



Defect Characterization - Methods



Methods used by RD50 Collaboration

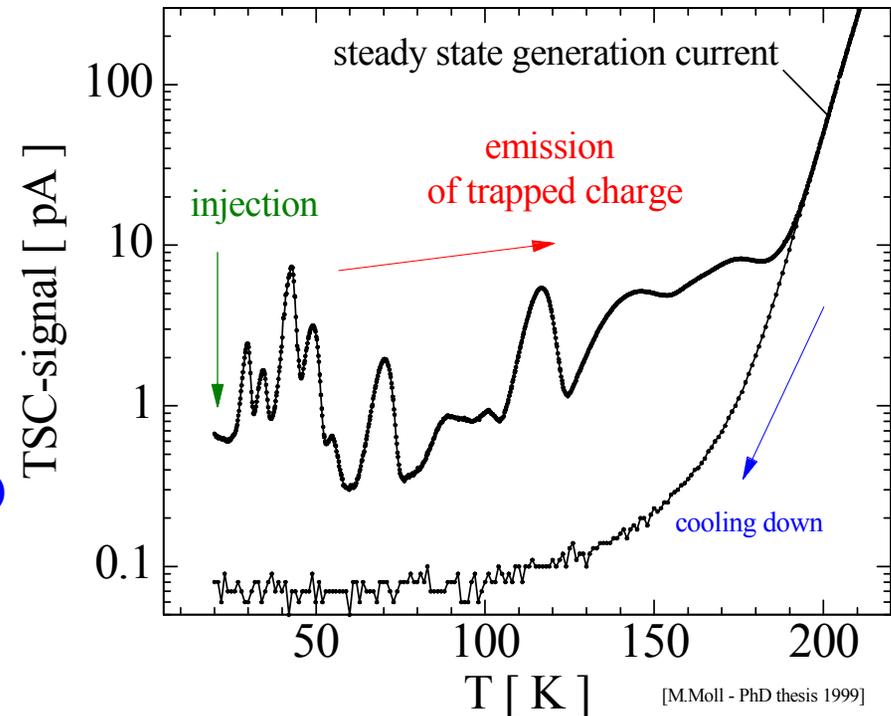
RD50-WODEAN project
guided by G.Lindstroem (HH):

- C-DLTS (Capacitance Deep Level Transient Spectroscopy)
- I-DLTS (Current Deep Level Transient Spectroscopy)
- TSC (Thermally Stimulated Currents)
- PITS (Photo Induced Transient Spectroscopy)
- FTIR (Fourier Transform Infrared Spectroscopy)
- RL (Recombination Lifetime Measurements)
- PC (Photo Conductivity Measurements)
- PL (Photo Luminescence)
- EPR (Electron Paramagnetic Resonance)
- TCT (Transient Charge Technique)
- CV/IV (Capacitance Voltage and Current Voltage Characteristics)

Further interesting methods:

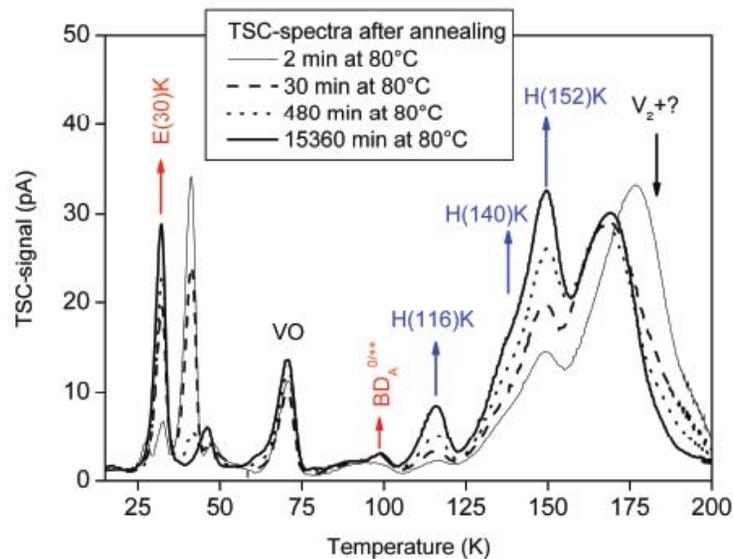
- Positron Annihilation, TEM, TSCAP,

TSC (Thermally Stimulated Currents)

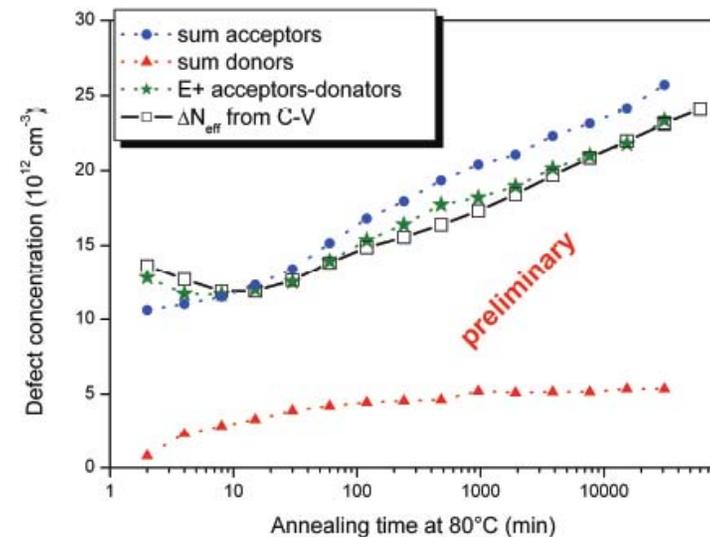


- TSC and CV measurements (Isothermal annealing after $2 \times 10^{14} \text{ n/cm}^2$)

TSC-results (EPI-ST)



comparison to ΔN_{eff}



- short term annealing well described
- microscopic results predict macroscopic findings!

[Alexandra Junkes, Hamburg University, RD50 Workshop June 2009]



Summary – defects with strong impact on the device properties at operating temperature

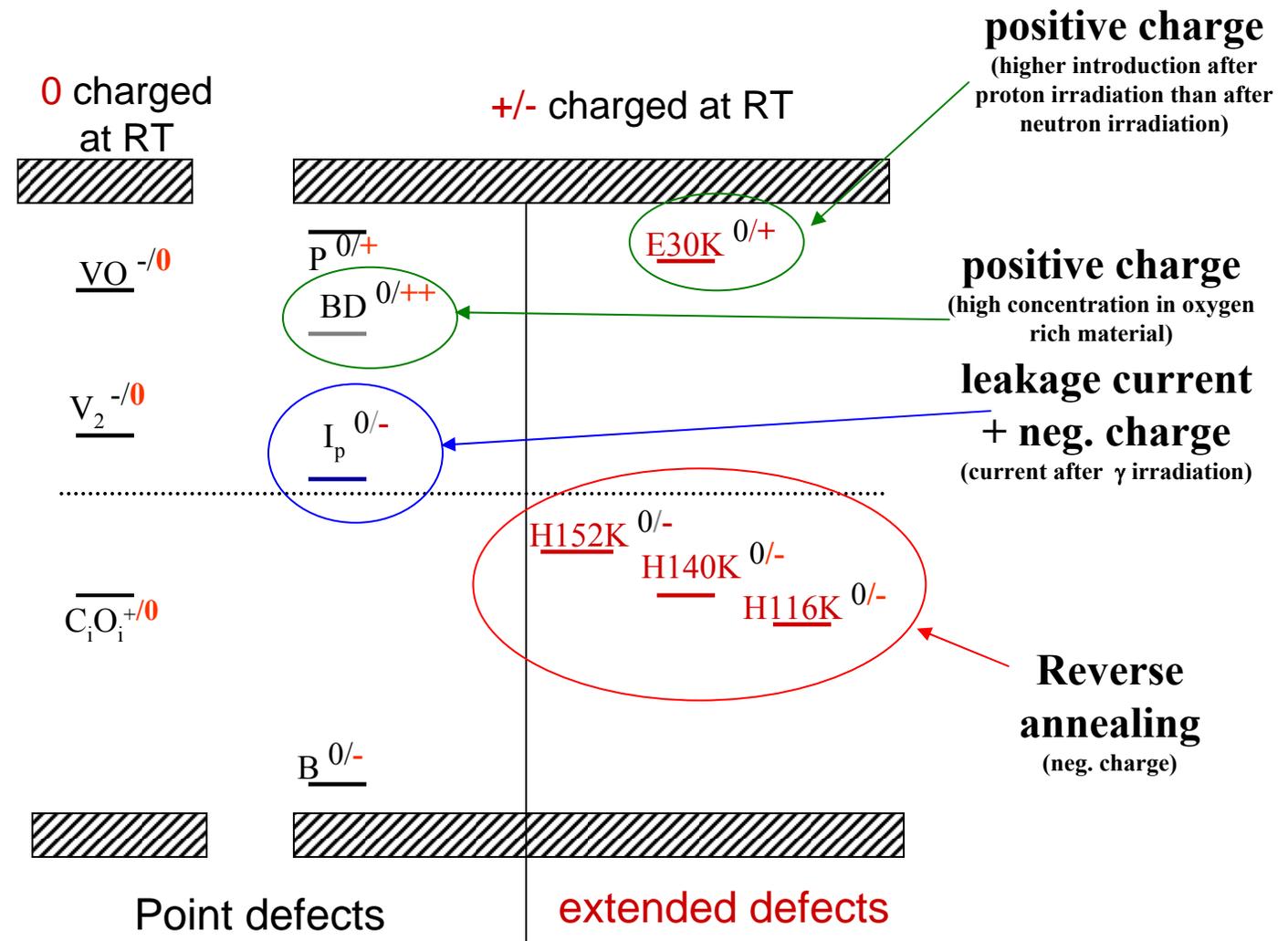


Point defects

- $E_i^{BD} = E_c - 0.225 \text{ eV}$
- $\sigma_n^{BD} = 2.3 \cdot 10^{-14} \text{ cm}^2$
- $E_i^I = E_c - 0.545 \text{ eV}$
 - $\sigma_n^I = 2.3 \cdot 10^{-14} \text{ cm}^2$
 - $\sigma_p^I = 2.3 \cdot 10^{-14} \text{ cm}^2$

Cluster related centers

- $E_i^{116K} = E_v + 0.33 \text{ eV}$
- $\sigma_p^{116K} = 4 \cdot 10^{-14} \text{ cm}^2$
- $E_i^{140K} = E_v + 0.36 \text{ eV}$
- $\sigma_p^{140K} = 2.5 \cdot 10^{-15} \text{ cm}^2$
- $E_i^{152K} = E_v + 0.42 \text{ eV}$
- $\sigma_p^{152K} = 2.3 \cdot 10^{-14} \text{ cm}^2$
- $E_i^{30K} = E_c - 0.1 \text{ eV}$
- $\sigma_n^{30K} = 2.3 \cdot 10^{-14} \text{ cm}^2$



[I.Pintilie et al., Appl. Phys. Lett.92 024101,2008]

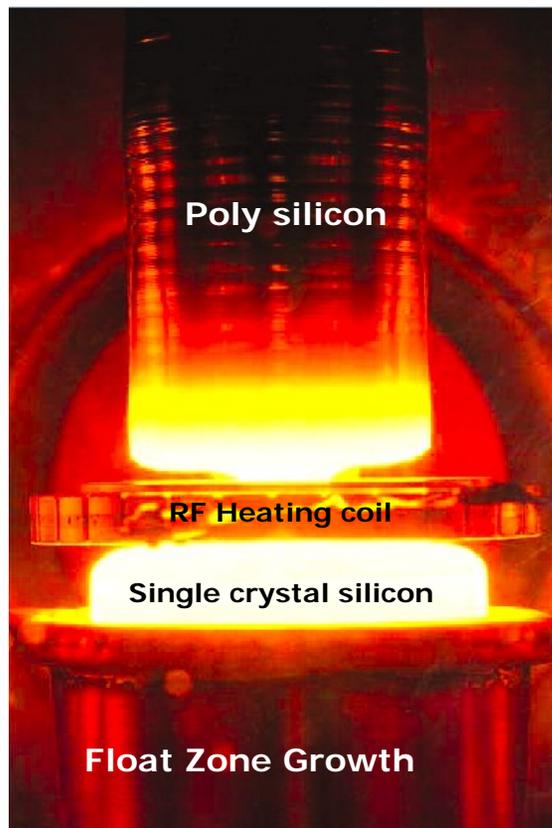


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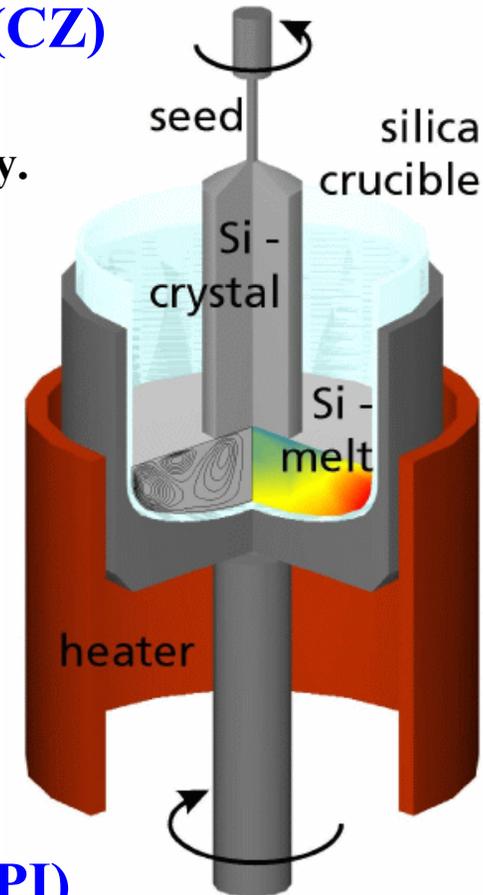
- **Floating Zone Silicon (FZ)**



- Basically all silicon tracking detectors made out of FZ silicon
- Some pixel sensors out of DOFZ Diffusion Oxygenated FZ silicon

- **Czochralski Silicon (CZ)**

- The growth method used by the IC industry.
- Difficult to produce very high resistivity



- **Epitaxial Silicon (EPI)**

- Chemical-Vapor Deposition (CVD) of Si
- up to 150 μm thick layers produced
- growth rate about 1 $\mu\text{m}/\text{min}$



Silicon Materials under Investigation by RD50



standard
for
particle
detectors

Material	Thickness [μm]	Symbol	ρ (Ωcm)	$[\text{O}_i]$ (cm^{-3})
Standard FZ (n- and p-type)	50,100,150, 300	FZ	$1-30 \times 10^3$	$< 5 \times 10^{16}$
Diffusion oxygenated FZ (n- and p-type)	300	DOFZ	$1-7 \times 10^3$	$\sim 1-2 \times 10^{17}$
Magnetic Czochralski Si, Okmetic, Finland (n- and p-type)	100, 300	MCz	$\sim 1 \times 10^3$	$\sim 5 \times 10^{17}$
Czochralski Si, Sumitomo, Japan (n-type)	300	Cz	$\sim 1 \times 10^3$	$\sim 8-9 \times 10^{17}$
Epitaxial layers on Cz-substrates, ITME, Poland (n- and p-type)	25, 50, 75, 100, 150	EPI	50 – 100	$< 1 \times 10^{17}$
Diffusion oxyg. Epitaxial layers on CZ	75	EPI-DO	50 – 100	$\sim 7 \times 10^{17}$

used for
LHC
Pixel
detectors

“new”
silicon
material

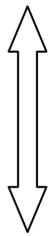
- **DOFZ silicon** - Enriched with oxygen on wafer level, inhomogeneous distribution of oxygen
- **CZ/MCZ silicon** - high O_i (oxygen) and O_{2i} (oxygen dimer) concentration (homogeneous)
- formation of shallow Thermal Donors possible
- **Epi silicon** - high O_i , O_{2i} content due to out-diffusion from the CZ substrate (inhomogeneous)
- thin layers: high doping possible (low starting resistivity)
- **Epi-Do silicon** - as EPI, however additional O_i diffused reaching homogeneous O_i content



FZ, DOFZ, Cz and MCz Silicon



- Strong differences in V_{dep}



- Standard FZ silicon
- Oxygenated FZ (DOFZ)
- CZ silicon and MCZ silicon

- Strong differences in internal electric field shape

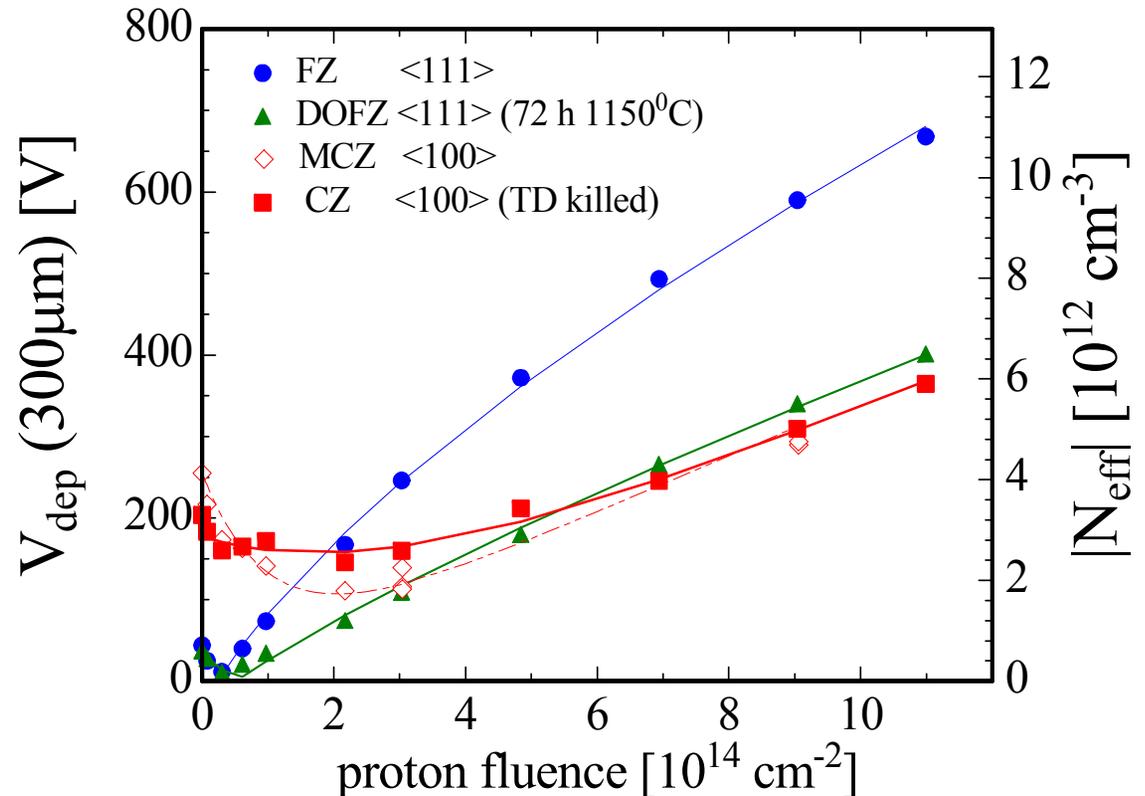
(space charge sign inversion, no inversion, double junction effects,...)



- Different impact on pad and strip detector operation!

- e.g.: a lower V_{dep} or $|N_{eff}|$ does not necessarily correspond to a higher CCE for strip detectors (see later)!

24 GeV/c proton irradiation (n-type silicon)

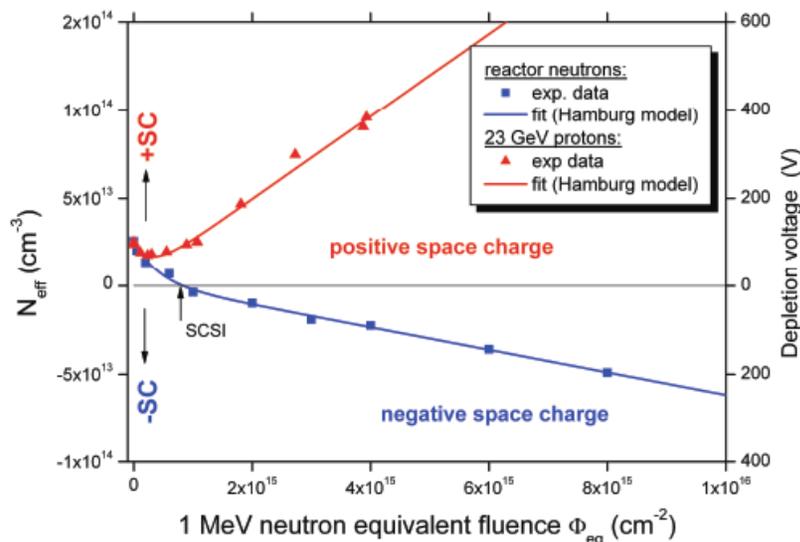


- Common to all materials (after hadron irradiation, not after γ irradiation):

- reverse current increase
- increase of trapping (electrons and holes) within $\sim 20\%$

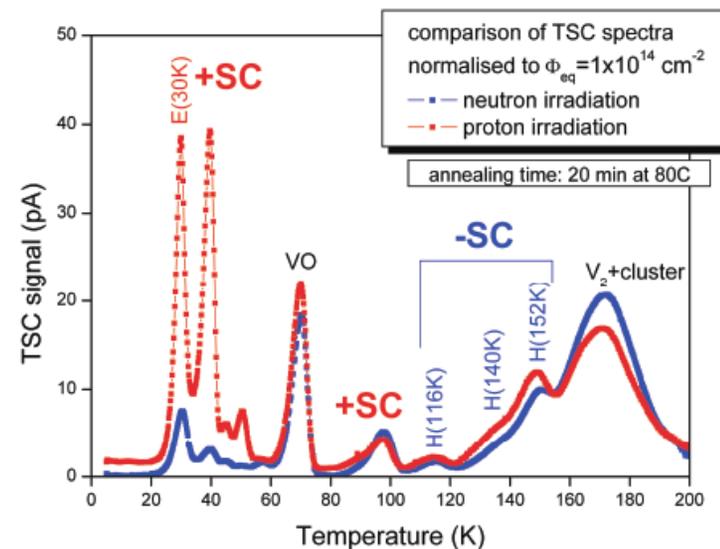
- **Epitaxial silicon irradiated with 23 GeV protons vs reactor neutrons**

development of N_{eff} for EPI-DO after neutron and proton irradiation



I. Pintilie, et al., to be published.

TSC results after neutron and proton irradiation



- SCSI after neutrons but not after protons
- donor generation enhanced after proton irradiation
- microscopic defects explain macroscopic effect at low Φ_{eq}

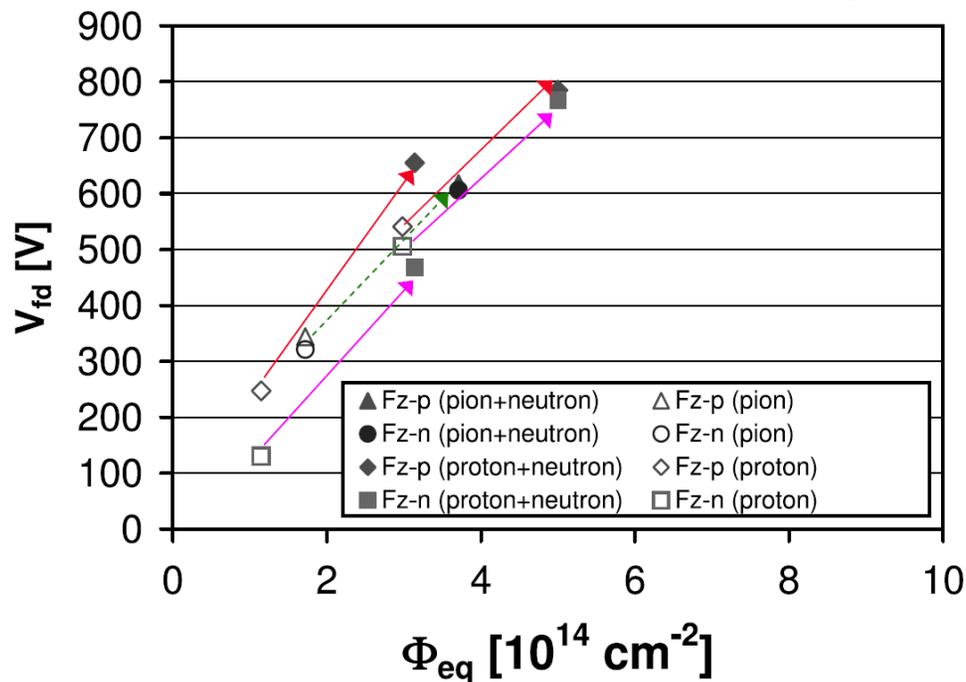


Mixed irradiations – Change of N_{eff}

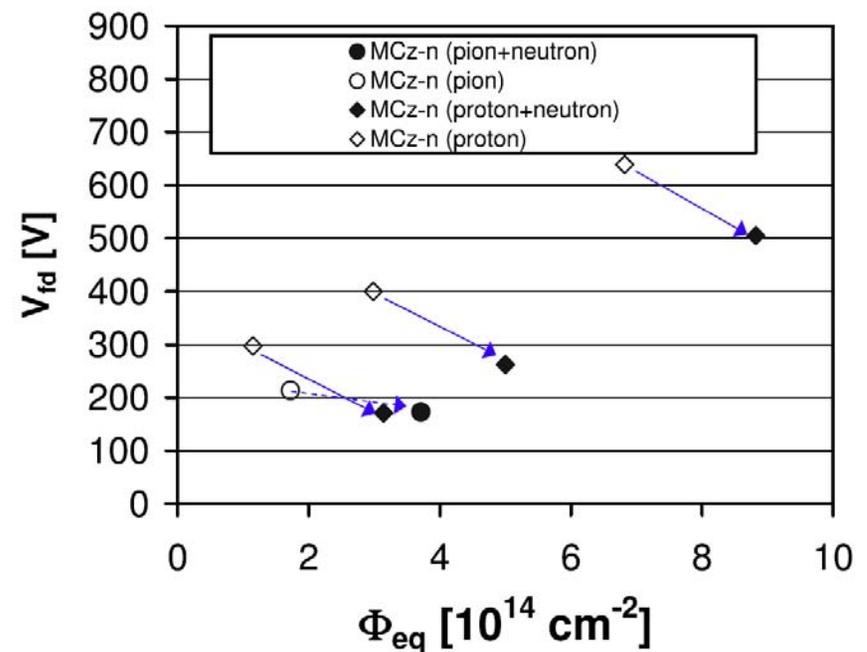


- Exposure of FZ & MCZ silicon sensors to ‘mixed’ irradiations
 - First step: Irradiation with protons or pions
 - Second step: Irradiation with neutrons

FZ: Accumulation of damage

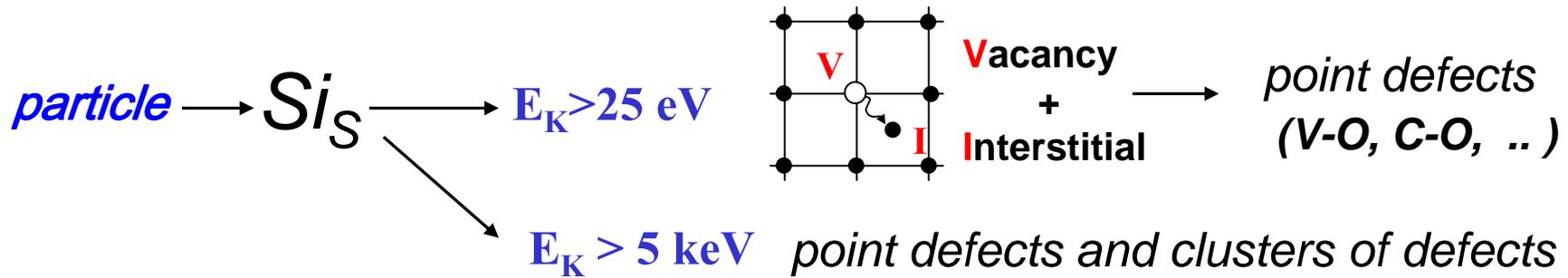


MCZ: Compensation of damage



[G.Kramberger et al., “Performance of silicon pad detectors after mixed irradiations with neutrons and fast charged hadrons”, NIMA 609 (2009) 142-148]

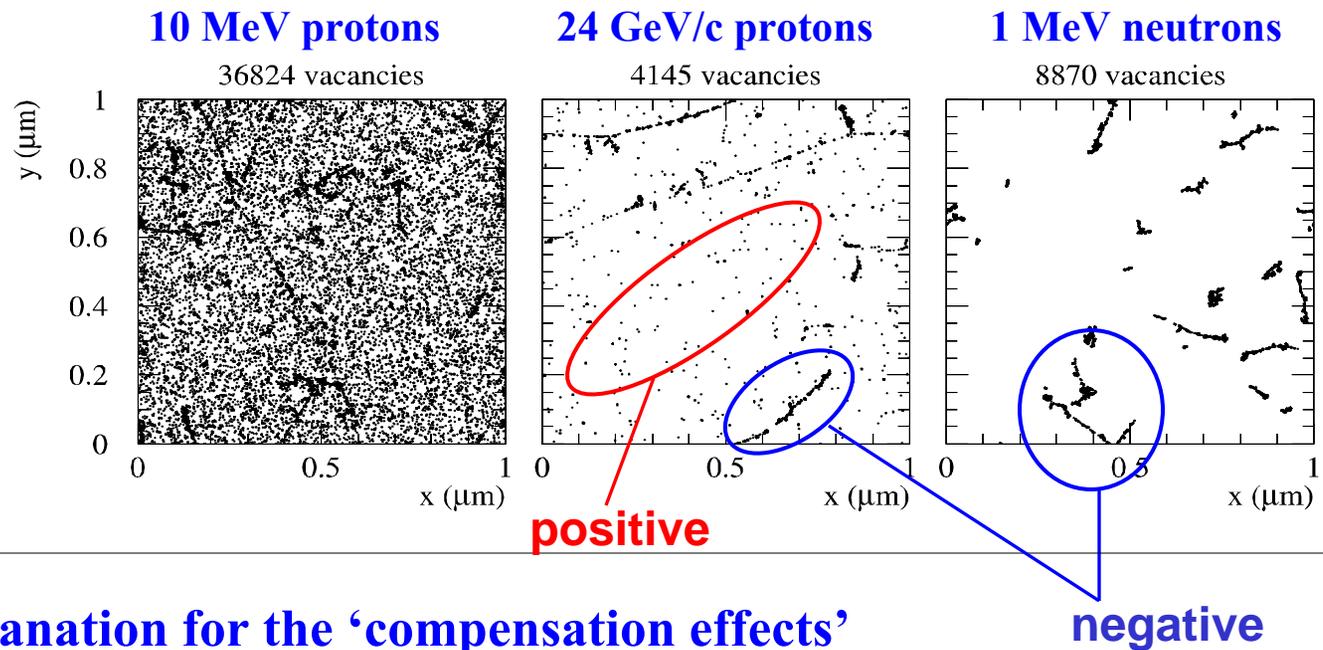
Why is proton and neutron damage different?



Simulation:

Initial distribution of vacancies in $(1\mu\text{m})^3$ after 10^{14} particles/cm²

[Mika Huhtinen NIMA 491(2002) 194]



- A ‘simplified’ explanation for the ‘compensation effects’
 - Defect clusters produce predominantly **negative space charge**
 - Point defects produce predominantly **positive space charge** (in ‘oxygen rich’ silicon)

For the experts: Note the NIEL violation

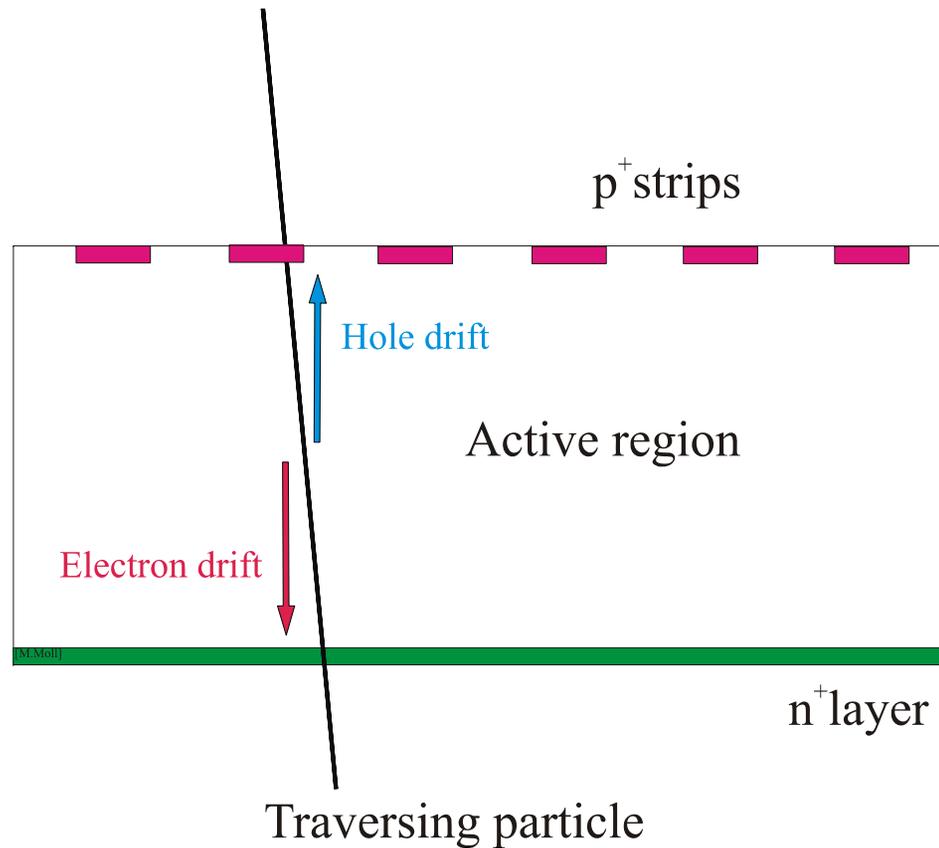


Advantage of non-inverting material

p-in-n detectors (schematic figures!)



Fully depleted detector
(non – irradiated):





Advantage of non-inverting material



p-in-n detectors (schematic figures!)

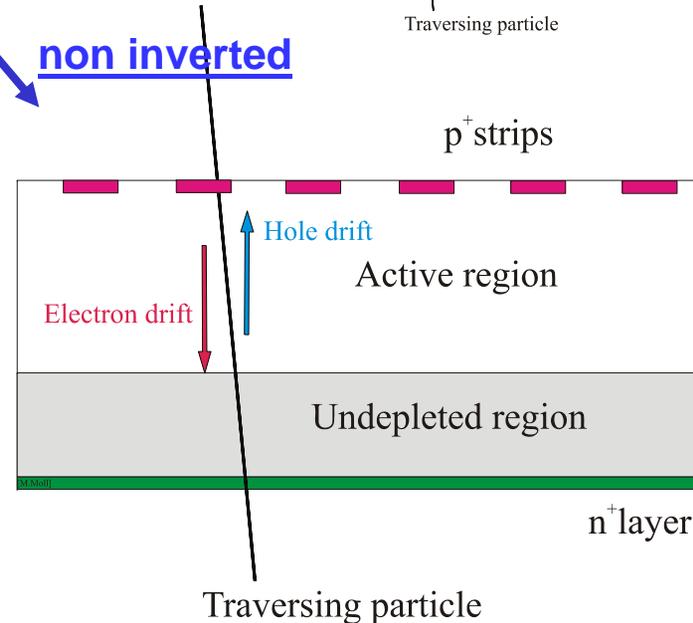
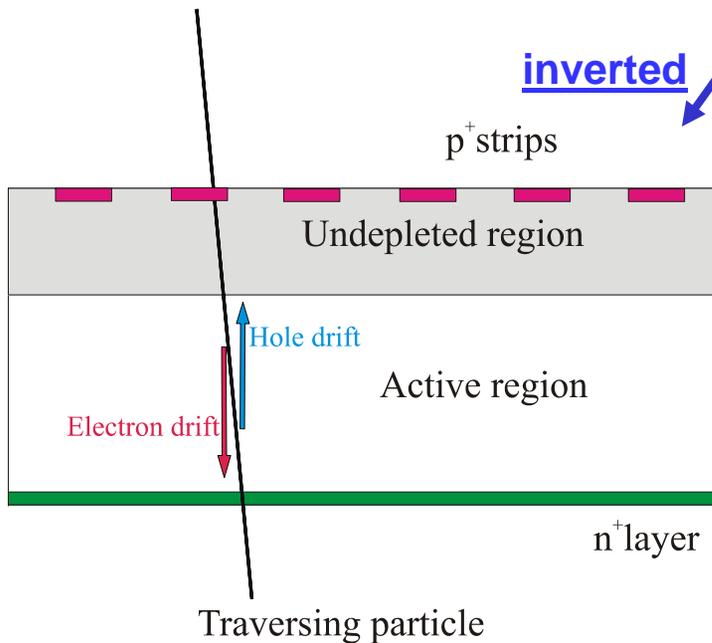
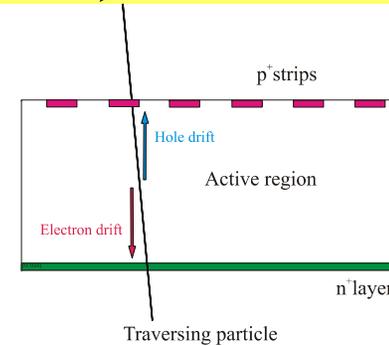
Be careful, this is a very schematic explanation, reality is more complex !

Fully depleted detector (non – irradiated):

heavy irradiation

inverted

non inverted



inverted to “p-type”, under-depleted:

- Charge spread – degraded resolution
- Charge loss – reduced CCE

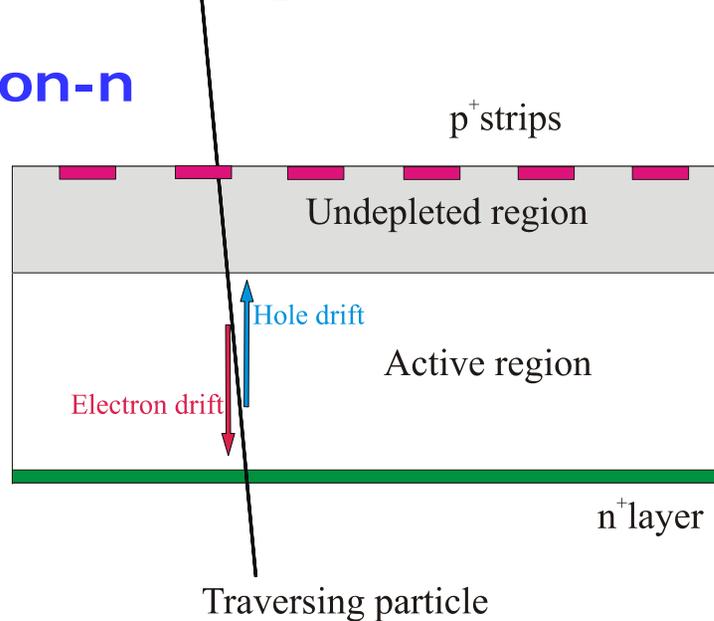
non-inverted, under-depleted:

- Limited loss in CCE
- Less degradation with under-depletion

p-in-n versus n-in-p (or n-in-n) detectors

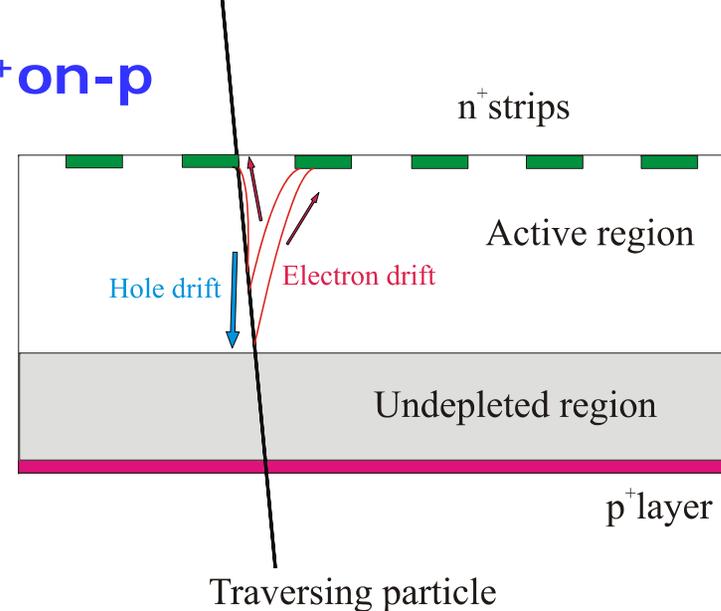
n-type silicon after high fluences:
(type inverted)

p⁺ on-n



p-type silicon after high fluences:
(still p-type)

n⁺ on-p



p-on-n silicon, under-depleted:

- Charge spread – degraded resolution
- Charge loss – reduced CCE

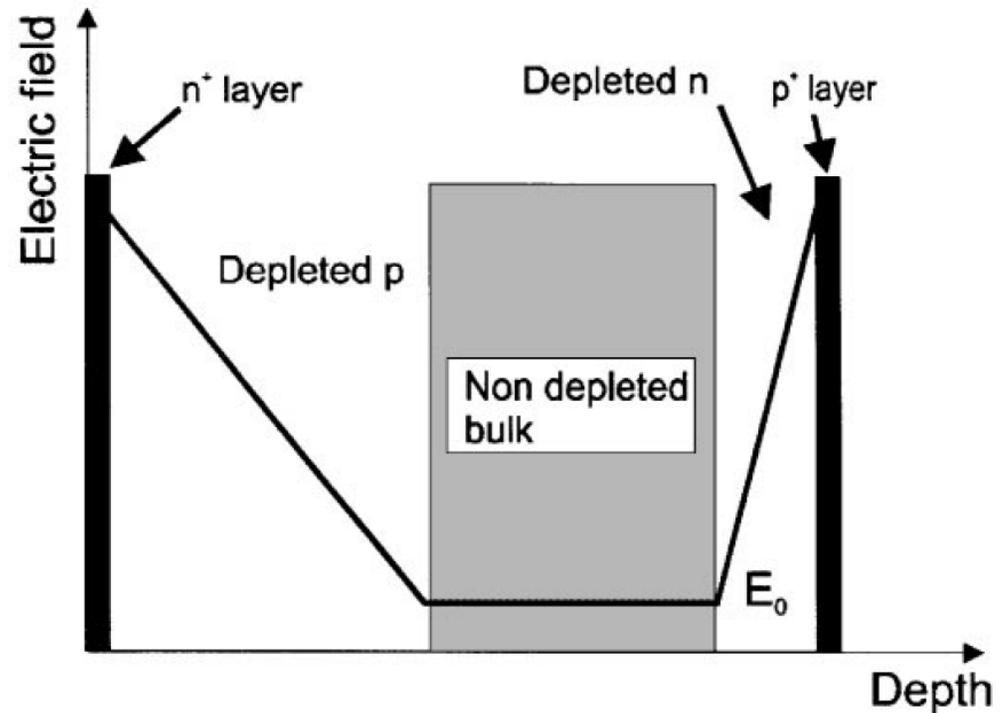
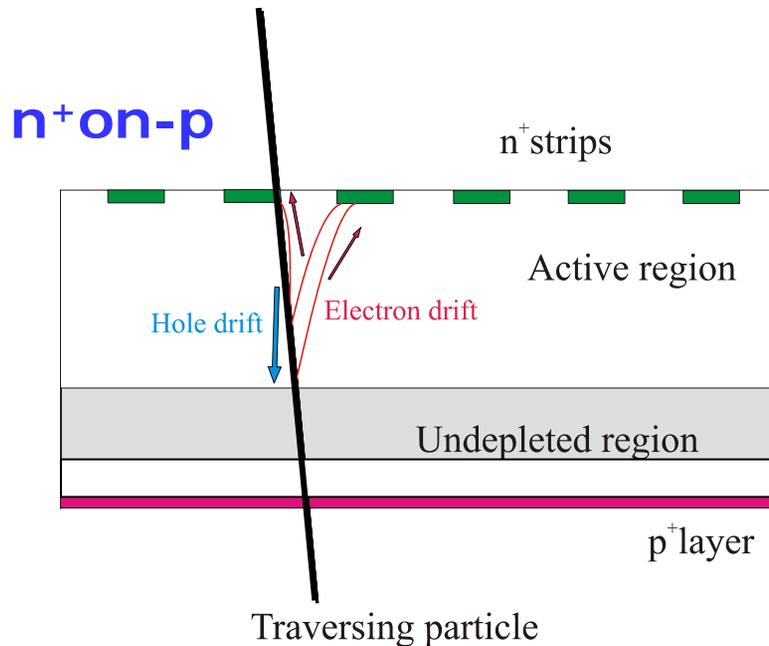
n-on-p silicon, under-depleted:

- Limited loss in CCE
- Less degradation with under-depletion
- Collect electrons (3 x faster than holes)

Comments:

- Instead of n-on-p also n-on-n devices could be used

p-type silicon after high fluences:
(still “p-type”)



- **Dominant junction close to n⁺ readout strip for FZ n-in-p**
- **For MCZ p-in-n even more complex fields have been reported:**
 - no “type inversion”(SCSI) = dominant field remains at p implant
 - “equal double junctions” with almost symmetrical fields on both sides

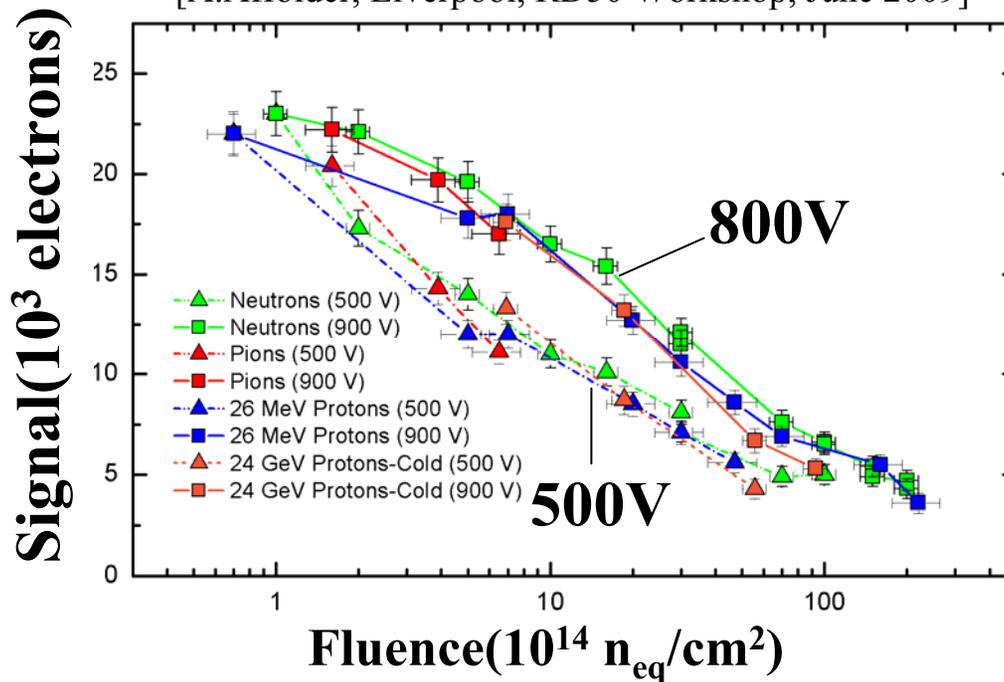


FZ n-in-p microstrip detectors (n, p, π – irradi)



- **n-in-p microstrip p-type FZ detectors** (Micron, 280 or 300 μ m thick, 80 μ m pitch, 18 μ m implant)
- **Detectors read-out with 40MHz** (SCT 128A)

[A.Affolder, Liverpool, RD50 Workshop, June 2009]



- **CCE: $\sim 7300e$ ($\sim 30\%$)**
after $\sim 1 \times 10^{16} cm^{-2}$ 800V
- **n-in-p sensors are strongly considered for ATLAS upgrade** (previously p-in-n used)

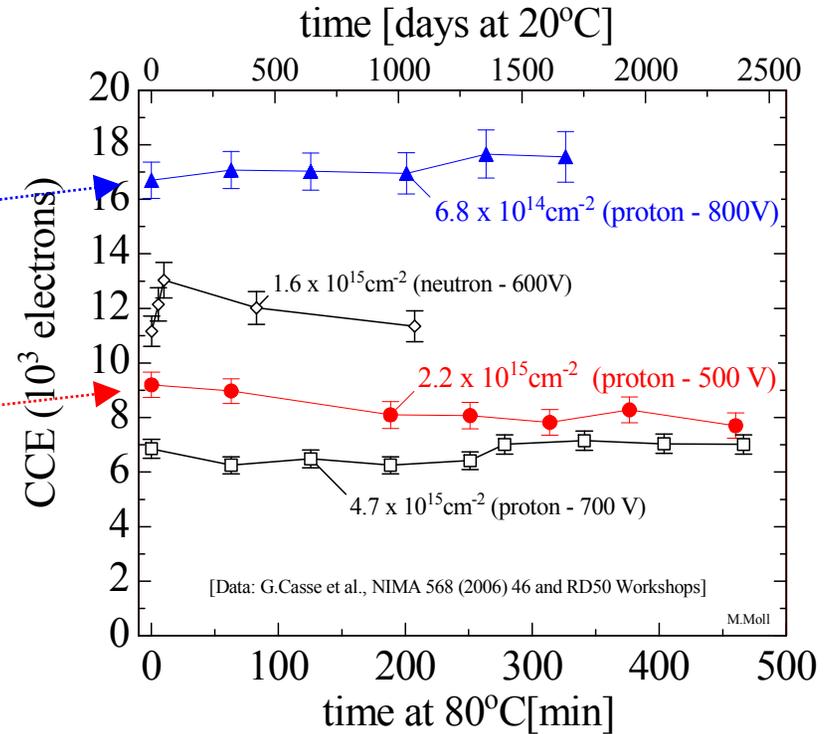
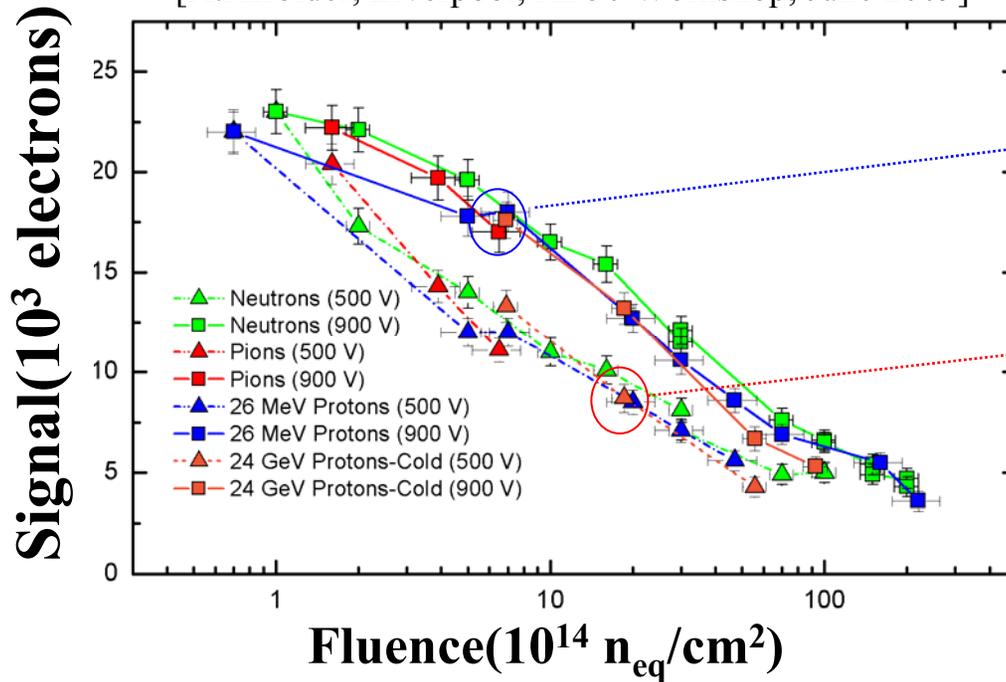


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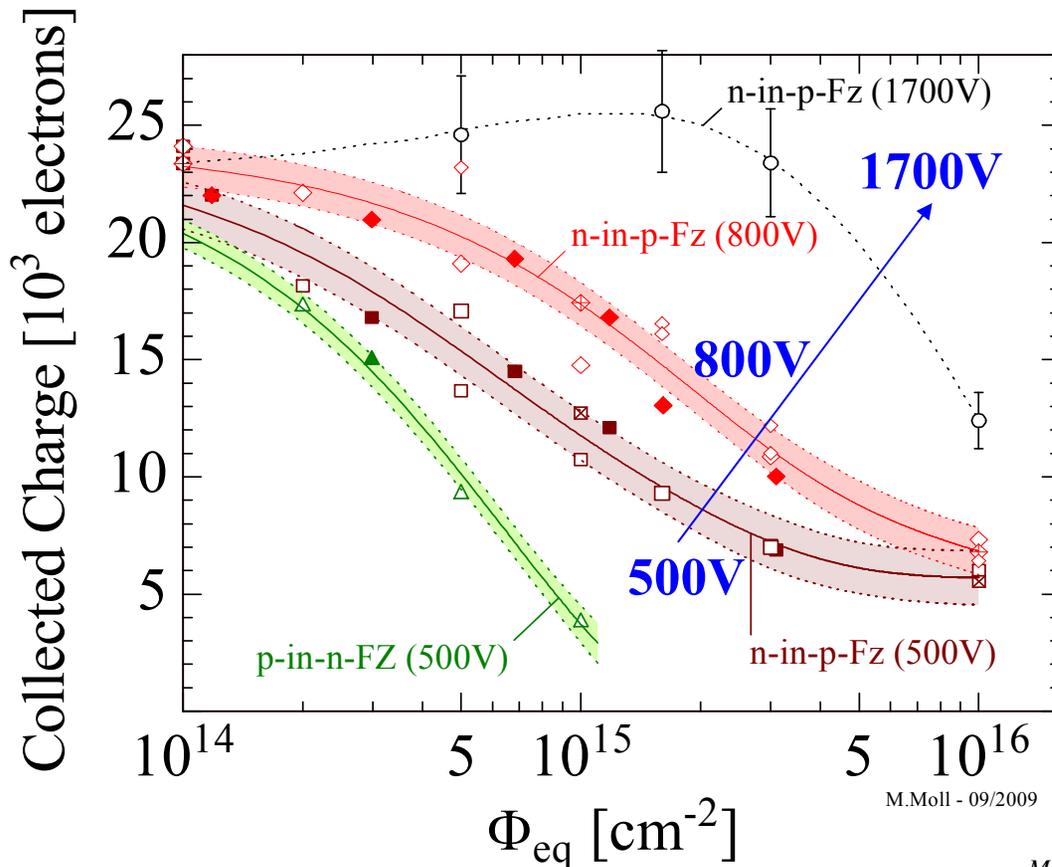


- **CCE: $\sim 7300e$ ($\sim 30\%$)**
after $\sim 1 \times 10^{16} cm^{-2}$ 800V
- **n-in-p sensors are strongly considered for ATLAS upgrade** (previously p-in-n used)

- **no reverse annealing in CCE measurements for neutron and proton irradiated detectors**

- Why do planar silicon sensors with n-strip readout give such high signals after high levels ($>10^{15} \text{ cm}^{-2} \text{ p/cm}^2$) of irradiation?

- Extrapolation of charge trapping parameters obtained at lower fluences would predict much lower signal!
- Assumption: ‘Charge multiplication effects’ as even $\text{CCE} > 1$ was observed



FZ Silicon Strip Sensors

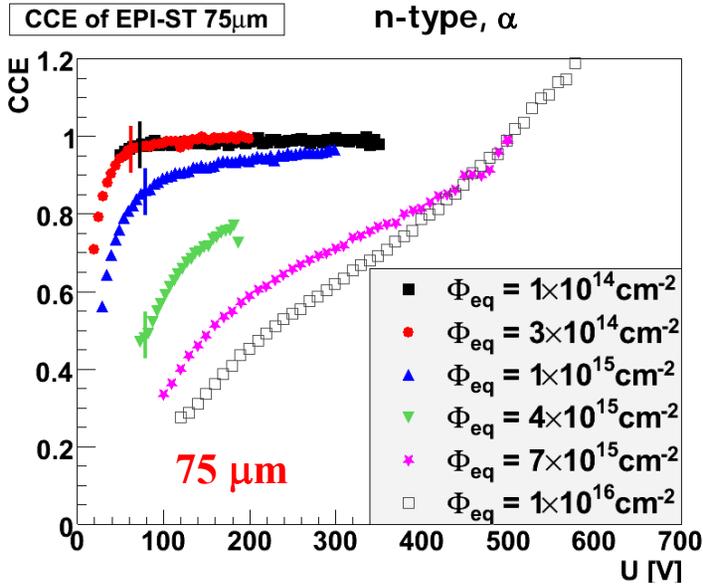
- n-in-p (FZ), 300 μm , 500V, 23GeV p [1]
- n-in-p (FZ), 300 μm , 500V, neutrons [1,2]
- ⊠ n-in-p (FZ), 300 μm , 500V, 26MeV p [1]
- ◆ n-in-p (FZ), 300 μm , 800V, 23GeV p [1]
- ◇ n-in-p (FZ), 300 μm , 800V, neutrons [1,2]
- ◊ n-in-p (FZ), 300 μm , 800V, 26MeV p [1]
- n-in-p (FZ), 300 μm , 1700V, neutrons [2]
- ▲ p-in-n (FZ), 300 μm , 500V, 23GeV p [1]
- △ p-in-n (FZ), 300 μm , 500V, neutrons [1]

References:

[1] G.Casse, VERTEX 2008
(p/n-FZ, 300 μm , (-30°C, 25ns)

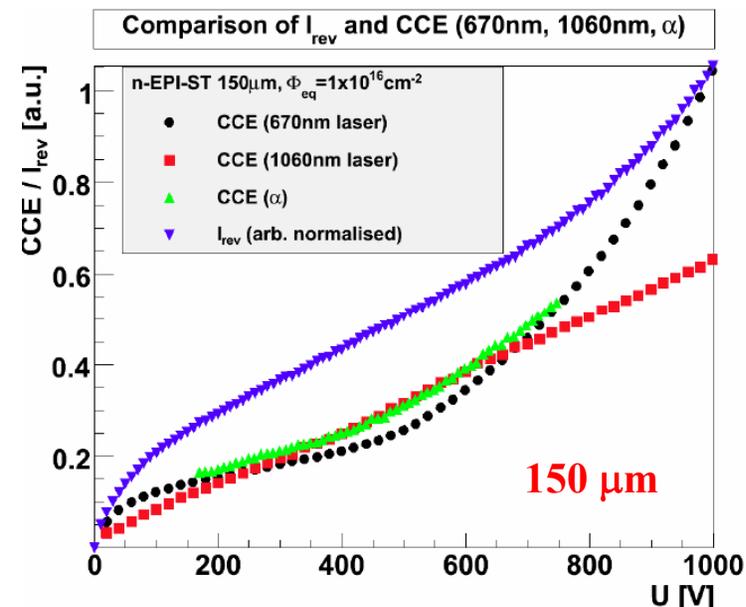
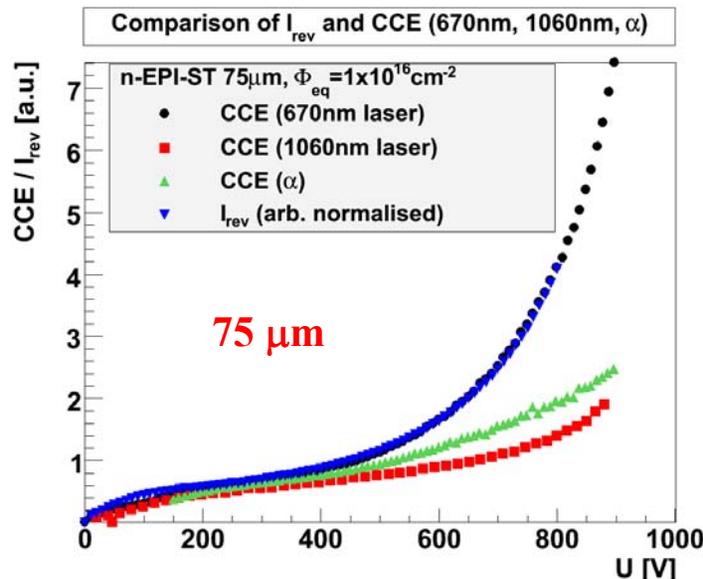
[2] I.Mandic et al., NIMA 603 (2009) 263
(p-FZ, 300 μm , -20°C to -40°C, 25ns)

- Which voltage can be applied?



[J.Lange et al., 14th RD50 Workshop, June 2009]

- Epi diodes, 75 and 150 μm thick
- Measured trapping probability found to be proportional to fluence and consistent with values extracted in FZ
- Multiplication effect stronger for 75 μm diodes
- Smaller penetration depth (670 nm laser) \rightarrow stronger charge multiplication



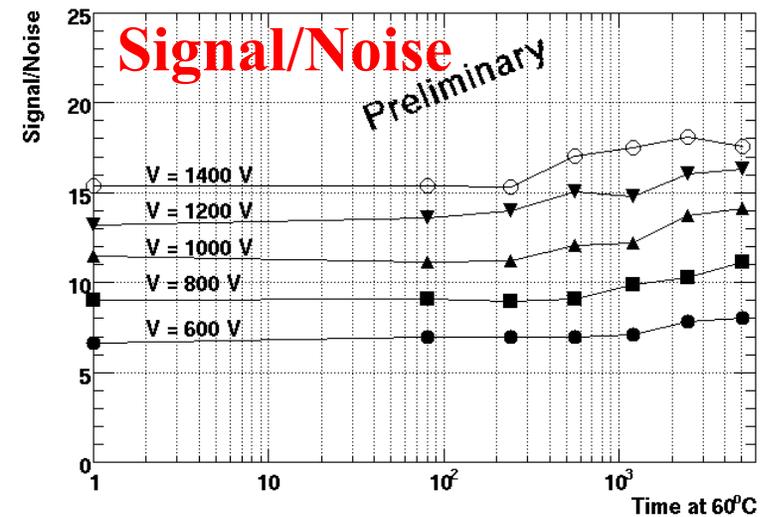
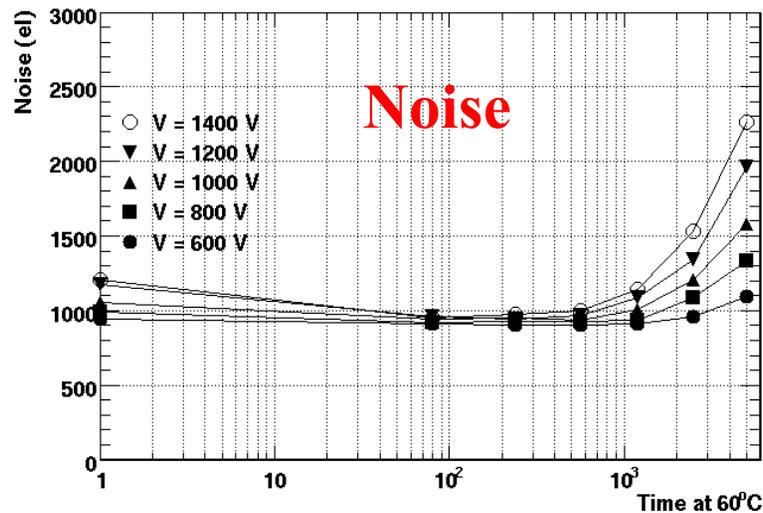
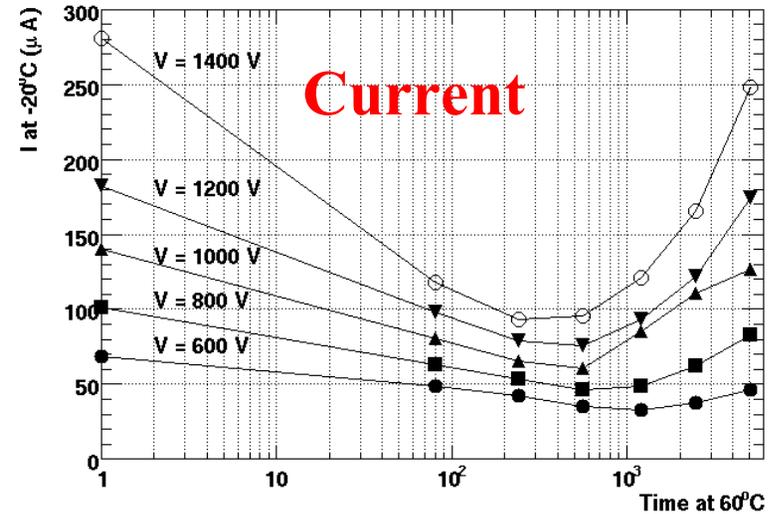
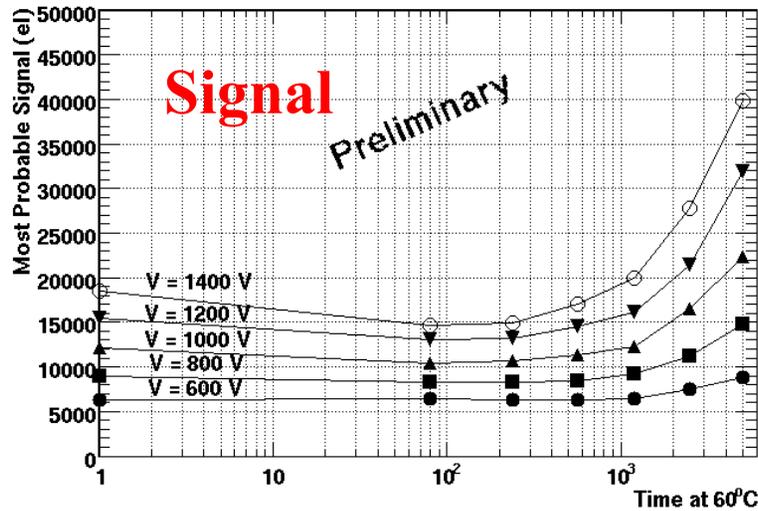


Annealing studies on strip sensors

[I.Mandic, 15th RD50 Workshop, Nov.09 – Measured on HPK ATLAS sensors]



- p-type strip sensor; $\Phi_{eq} = 5 \times 10^{15} \text{ cm}^{-2}$ (neutrons) [ATLAS – HPK – sensors]





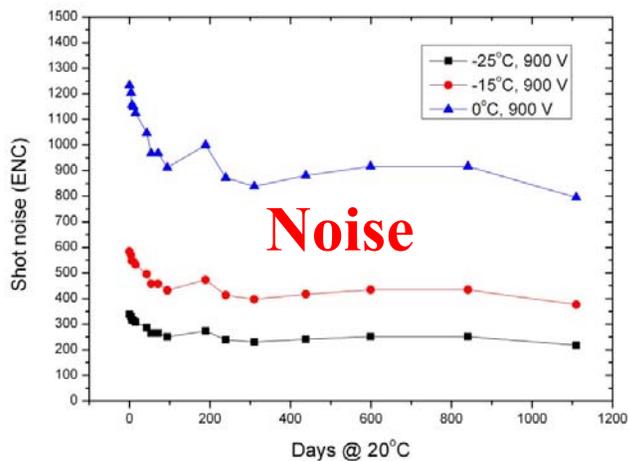
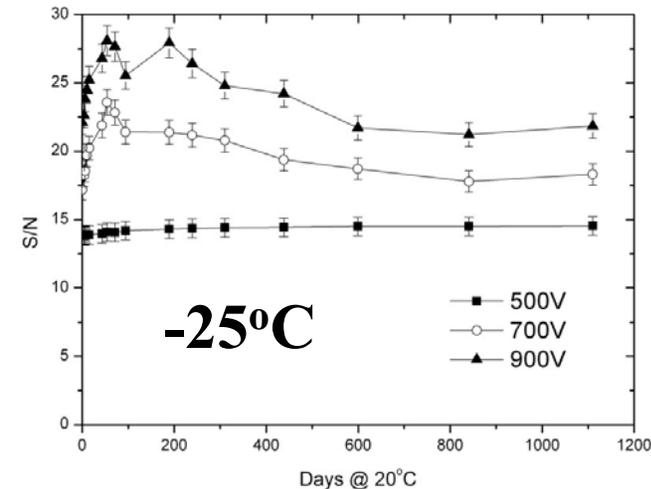
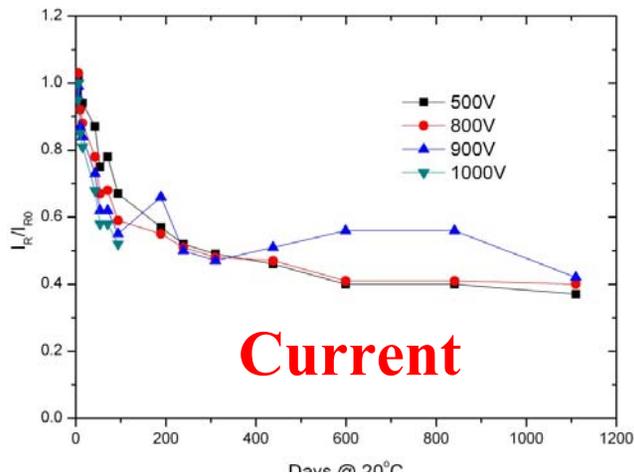
Further annealing studies



[G.Casse, Trento Workshop, Feb.2010 – Measured on HPK ATLAS sensors]

- p-type strip sensor; [ATLAS – HPK]
- $\Phi_{eq} = 1 \times 10^{15} \text{ n}_{eq} \text{ cm}^{-2}$ (26MeV protons)

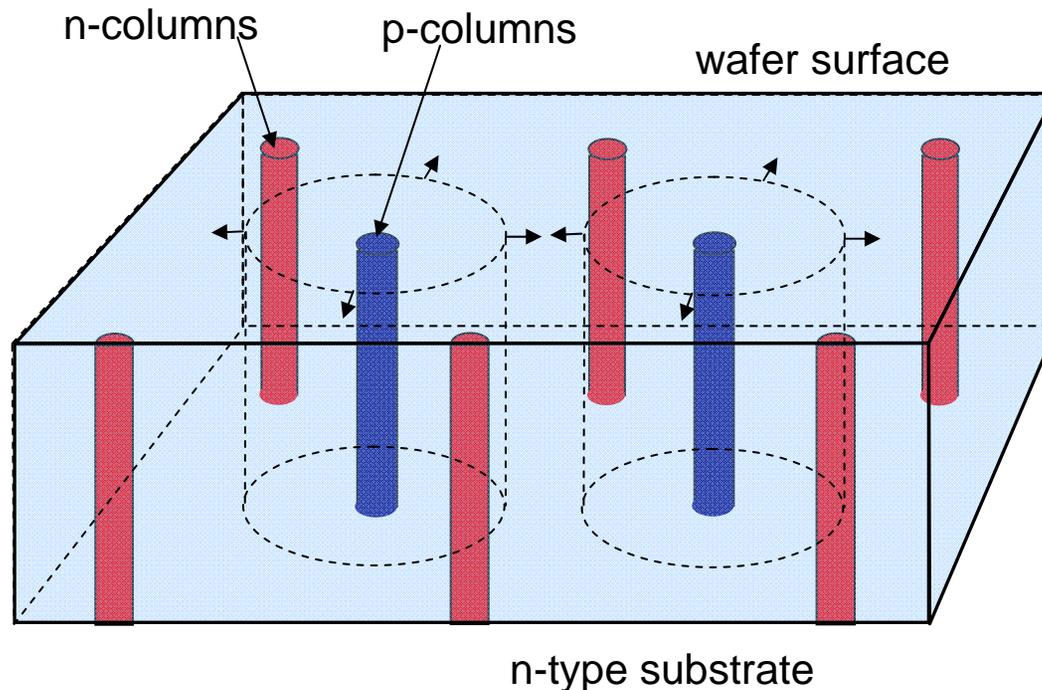
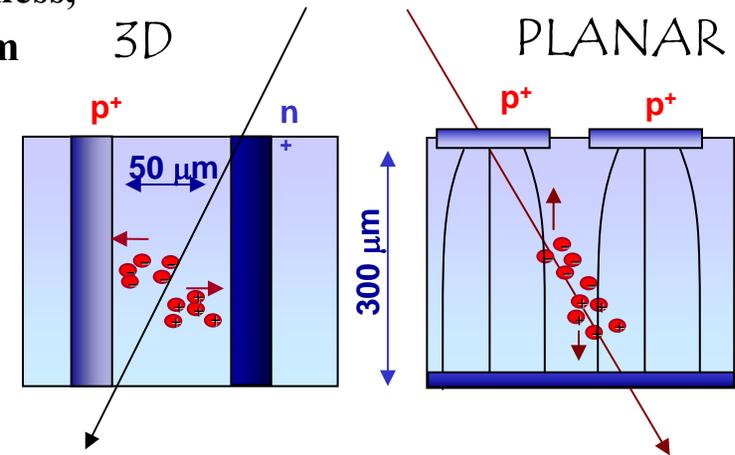
Signal to Noise



- Stable operation of n-in-p sensors without cooling during maintenance periods seems feasible
- Still long way to fully understand high voltage operation of highly irradiated sensors

3D detector - concept

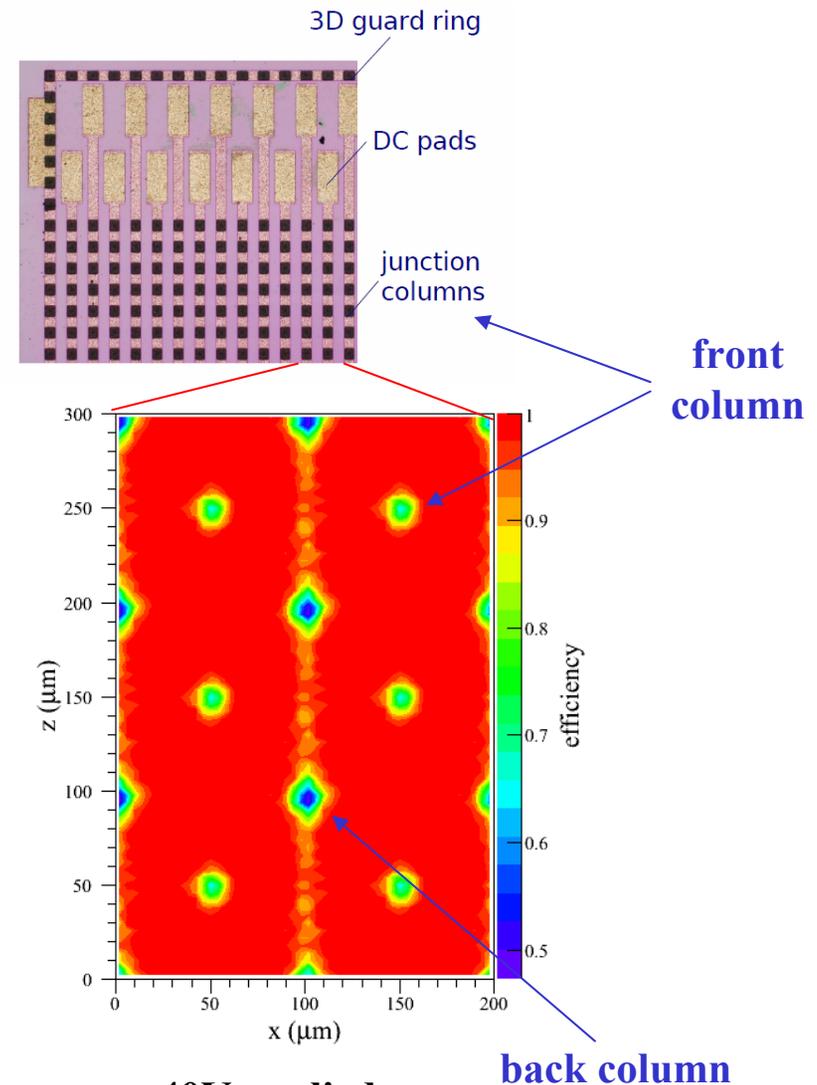
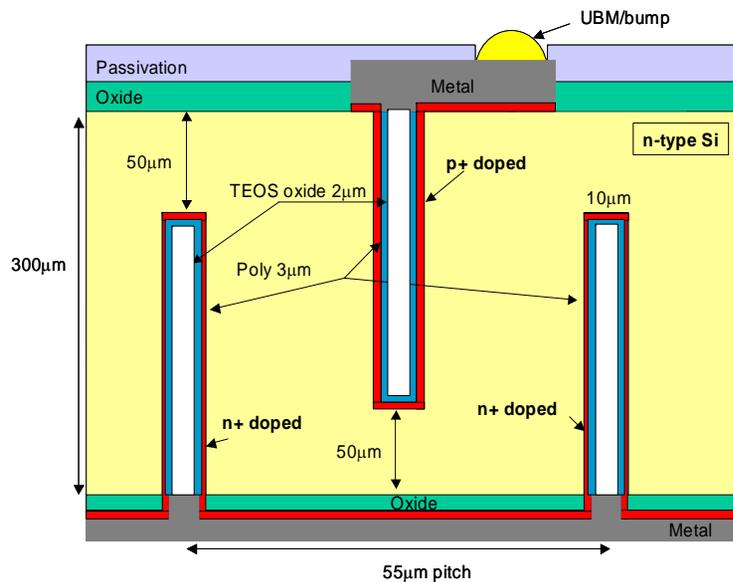
- **“3D” electrodes:** - narrow columns along detector thickness,
- diameter: $10\mu\text{m}$, distance: $50 - 100\mu\text{m}$
- **Lateral depletion:** - lower depletion voltage needed
- thicker detectors possible
- fast signal
- radiation hard



**Not discussed here in detail:
Seminar on 9. April dedicated
entirely to 3D sensors**

- **DDTC – Double sided double type column**

[G.Fleta, RD50 Workshop, June 2007]

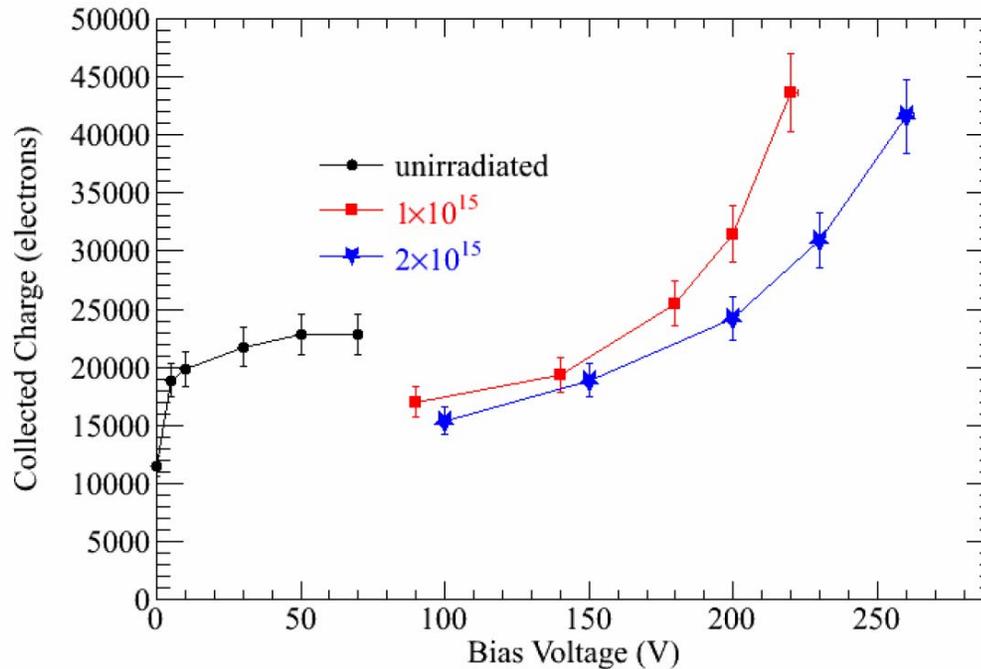


40V applied
~98% efficiency

- **Testbeam data – Example: efficiency map**
[M.Koehler, Freiburg Uni, RD50 Workshop June 09]
- **Processing of 3D sensors is challenging, but many good devices with reasonable production yield produced.**
- **Competing e.g. for ATLAS IBL pixel sensors**

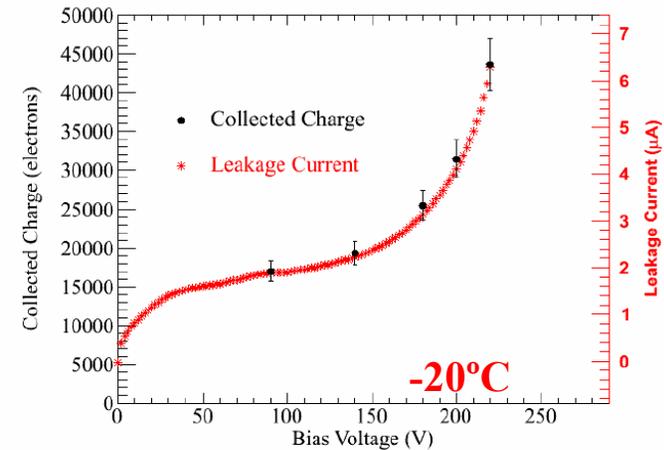
[M.Koehler, Trento Workshop, Feb. 2009]

- **DDTC sensors irradiated with 26 MeV protons**

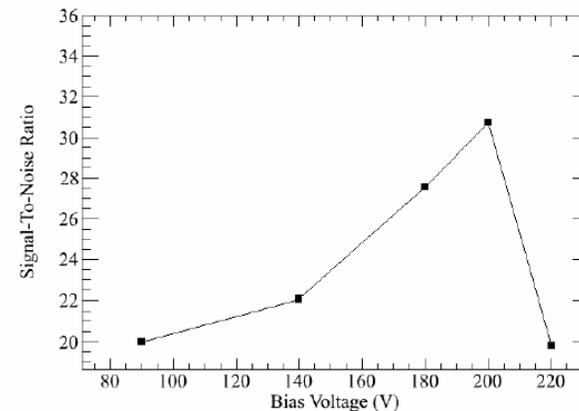


- **Avalanche effects in 3D sensors**

1×10^{15} n_{eq}/cm²



- **Signal scales with leakage current**



- **Signal to Noise**



Use of other semiconductor materials?



Property	Diamond	GaN	4H SiC	Si
E_g [eV]	5.5	3.39	3.3	1.12
$E_{\text{breakdown}}$ [V/cm]	10^7	$4 \cdot 10^6$	$2.2 \cdot 10^6$	$3 \cdot 10^5$
μ_e [cm^2/Vs]	1800	1000	800	1450
μ_h [cm^2/Vs]	1200	30	115	450
v_{sat} [cm/s]	$2.2 \cdot 10^7$	-	$2 \cdot 10^7$	$0.8 \cdot 10^7$
e-h energy [eV]	13	8.9	7.6-8.4	3.6
e-h pairs/ X_0	4.4	~2-3	4.5	10.1

- **Diamond: wider bandgap**
 ⇒ lower leakage current
 ⇒ less cooling needed

- **Signal produced by m.i.p:**
 Diamond 36 e/ μm
 Si 89 e/ μm
 ⇒ Si gives more charge than diamond

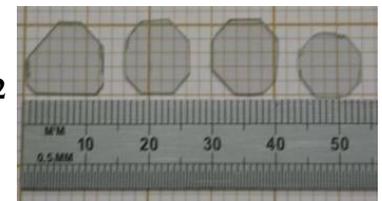
- **GaAs, SiC and GaN** ⇒ strong radiation damage observed
 ⇒ no potential material for sLHC detectors
 (*judging on the investigated material*)

- **Diamond (RD42)** ⇒ good radiation tolerance (*see later*)
 ⇒ already used in LHC beam condition monitoring systems
 ⇒ considered as potential detector material for sLHC pixel sensors

poly-CVD Diamond
 –16 chip ATLAS
 pixel module



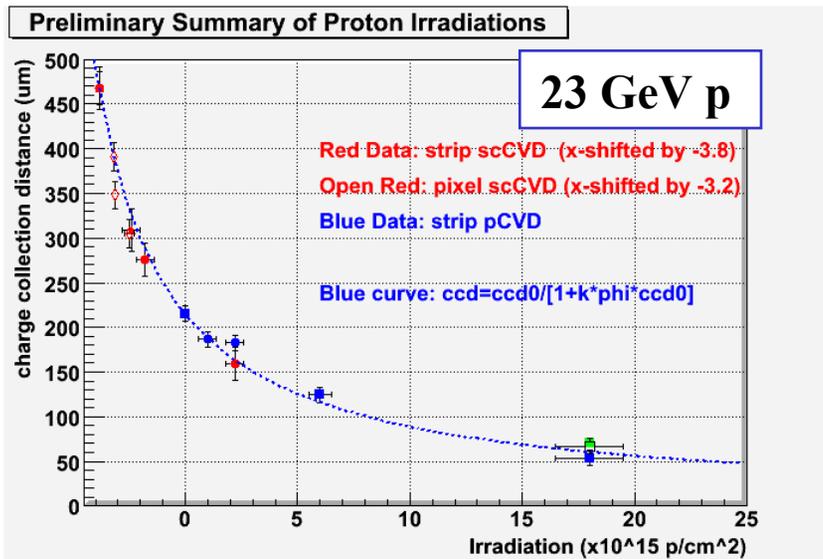
single crystal CVD
 Diamond of few cm^2



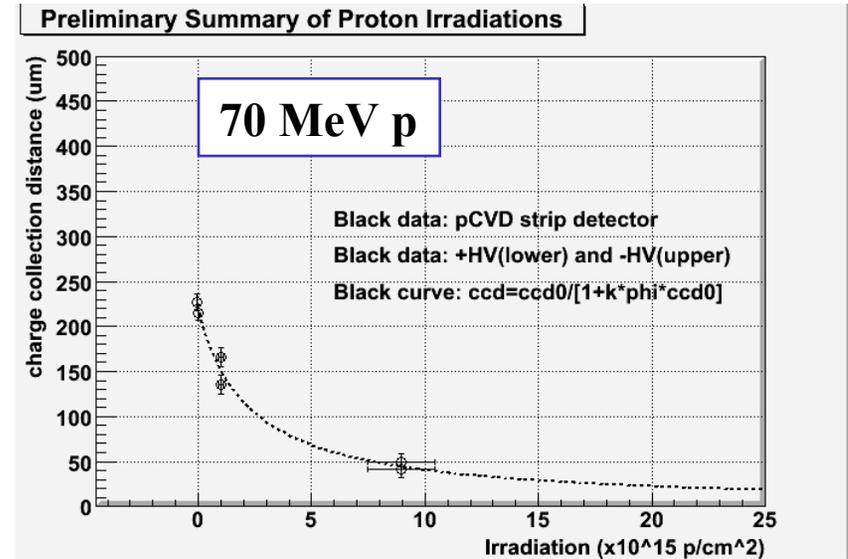
**Diamond sensors are heavily used in
 LHC Experiments for Beam Monitoring**



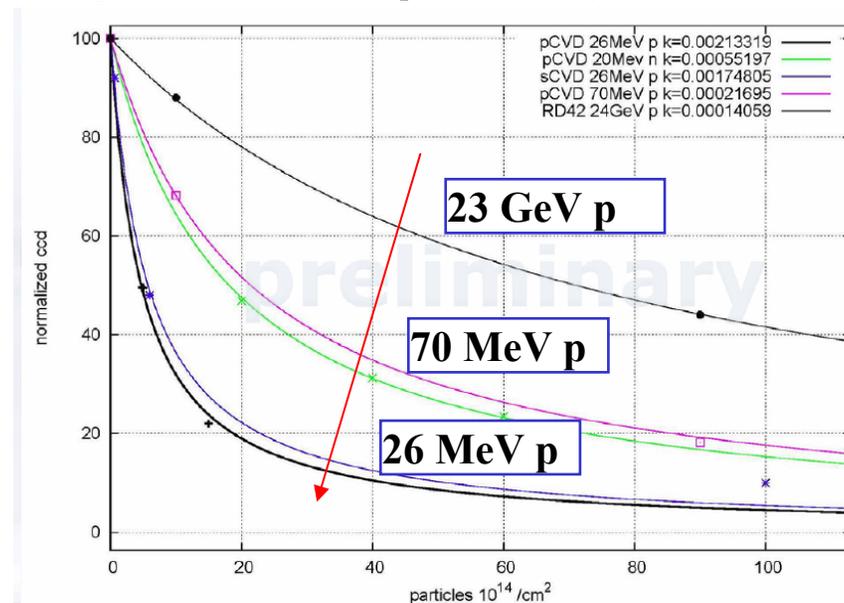
Are diamond sensor radiation hard?



[RD42, LHCC Status Report, Feb. 2010]



[RD42, LHCC Status Report, Feb. 2010]



[V.Rylov, CERN ESE Seminar 9.11.2009]

- Most published results on 23 GeV protons
- 70 MeV protons 3 times more damaging than 23 GeV protons
- 25 MeV protons seem to be even more damaging (Preliminary: RD42 about to cross check the data shown to the left)
- In line with NIEL calc. for Diamond [W. de Boer et al. Phys.Status Solidi 204:3009,2007]



Outline



- **Motivation to develop radiation harder detectors**
 - Super-LHC and expected radiation levels at the Super-LHC
 - Radiation induced degradation of detector performance
- **Radiation Damage in Silicon Detectors**
 - Macroscopic damage (changes in detector properties)
 - Microscopic damage (crystal damage)
- **Approaches to obtain radiation hard sensors**
 - **Material Engineering**
 - Silicon materials – FZ, MCZ, DOFZ, EPI
 - Other semiconductors
 - **Device Engineering**
 - p-in-n, n-in-n and n-in-p sensors
 - 3D sensors and thin devices
- **Silicon Sensors for the LHC upgrade**
 - **Collected Charge – Signal to Noise – Avalanche effects**
 - **Mixed irradiations**
- **Summary**

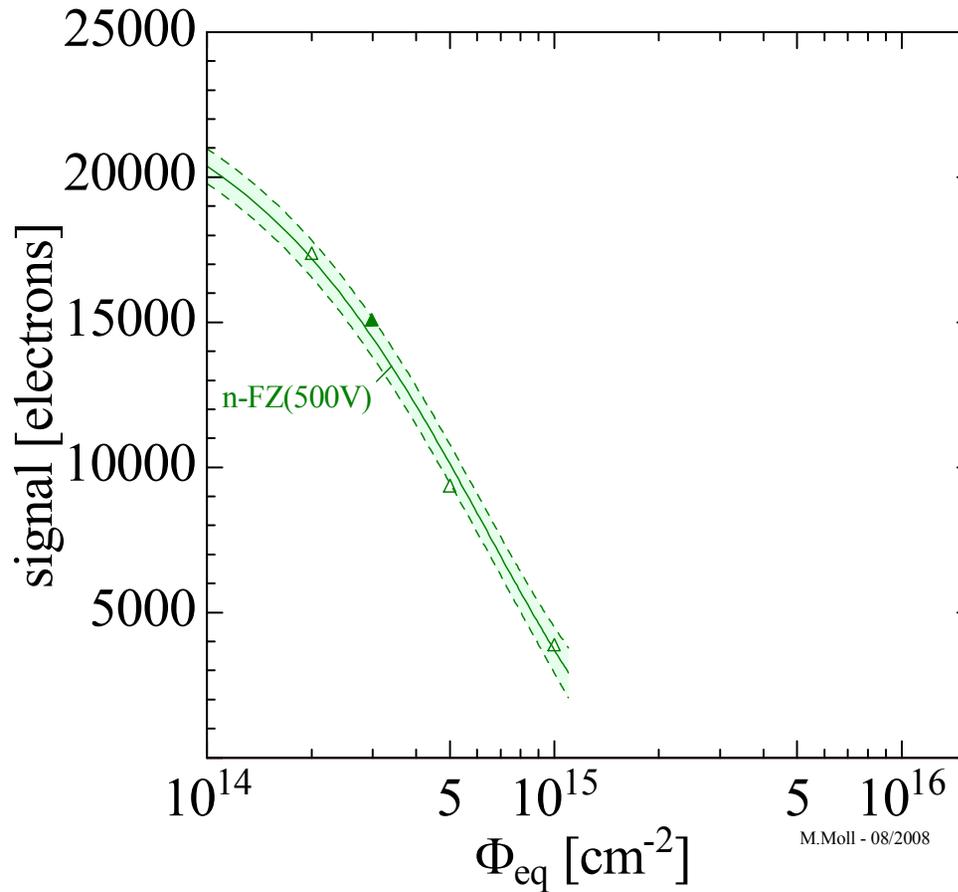


Silicon materials for Tracking Sensors



• Signal comparison for various Silicon sensors

Note: Measured partly under different conditions!
Lines to guide the eye (no modeling)!



Silicon Sensors

- ▲ p-in-n (FZ), 300μm, 500V, 23GeV p [1]
- △ p-in-n (FZ), 300μm, 500V, neutrons [1]

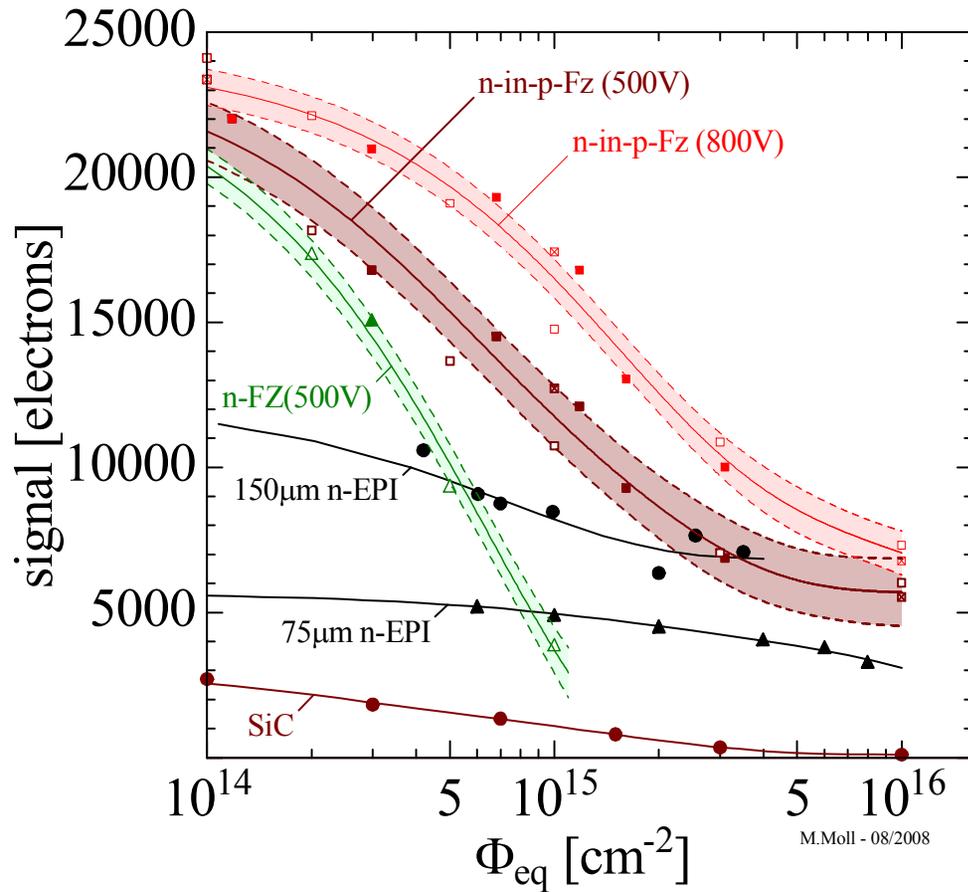
Other materials

References:

- [1] p/n-FZ, 300μm, (-30°C, 25ns), strip [Casse 2008]
- [2] p-FZ, 300μm, (-40°C, 25ns), strip [Mandic 2008]
- [3] n-SiC, 55μm, (2μs), pad [Moscatelli 2006]
- [4] pCVD Diamond, scaled to 500μm, 23 GeV p, strip [Adam et al. 2006, RD42]
- Note: Fluence normalized with damage factor for Silicon (0.62)
- [5] 3D, double sided, 250μm columns, 300μm substrate [Pennicard 2007]
- [6] n-EPI, 75μm, (-30°C, 25ns), pad [Kramberger 2006]
- [7] n-EPI, 150μm, (-30°C, 25ns), pad [Kramberger 2006]
- [8] n-EPI, 150μm, (-30°C, 25ns), strip [Messineo 2007]

• Signal comparison for various Silicon sensors

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Lines to guide the eye (no modeling)!



Silicon Sensors

- p-in-n (EPI), 150 μm [7,8]
- ▲ p-in-n (EPI), 75μm [6]
- n-in-p (FZ), 300μm, 500V, 23GeV p [1]
- n-in-p (FZ), 300μm, 500V, neutrons [1]
- ⊠ n-in-p (FZ), 300μm, 500V, 26MeV p [1]
- n-in-p (FZ), 300μm, 800V, 23GeV p [1]
- n-in-p (FZ), 300μm, 800V, neutrons [1]
- ⊠ n-in-p (FZ), 300μm, 800V, 26MeV p [1]
- ▲ p-in-n (FZ), 300μm, 500V, 23GeV p [1]
- △ p-in-n (FZ), 300μm, 500V, neutrons [1]

Other materials

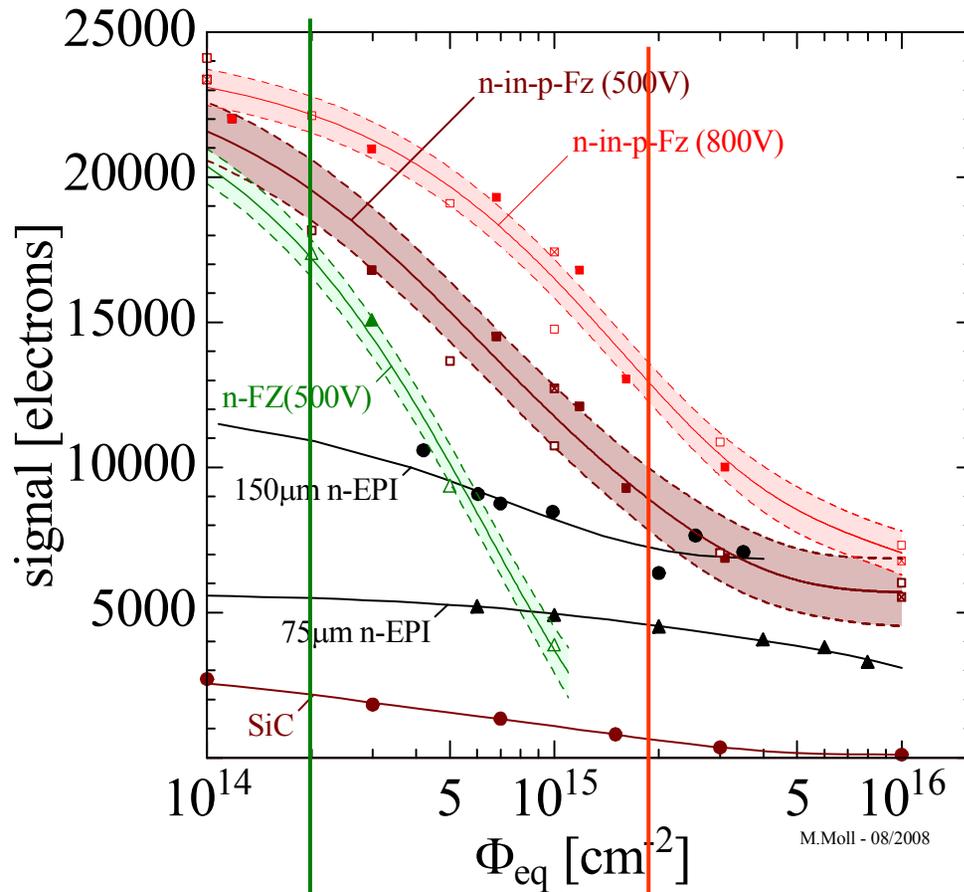
- SiC, n-type, 55 μm, 900V, neutrons [3]

References:

- [1] p/n-FZ, 300μm, (-30°C, 25ns), strip [Casse 2008]
- [2] p-FZ, 300μm, (-40°C, 25ns), strip [Mandic 2008]
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• Signal comparison for various Silicon sensors

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Lines to guide the eye (no modeling)!



- ### Silicon Sensors
- p-in-n (EPI), 150 µm [7,8]
 - ▲ p-in-n (EPI), 75µm [6]
 - n-in-p (FZ), 300µm, 500V, 23GeV p [1]
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 - n-in-p (FZ), 300µm, 500V, 26MeV p [1]
 - n-in-p (FZ), 300µm, 800V, 23GeV p [1]
 - n-in-p (FZ), 300µm, 800V, neutrons [1]
 - n-in-p (FZ), 300µm, 800V, 26MeV p [1]
 - ▲ p-in-n (FZ), 300µm, 500V, 23GeV p [1]
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- ### Other materials
- SiC, n-type, 55 µm, 900V, neutrons [3]

References:

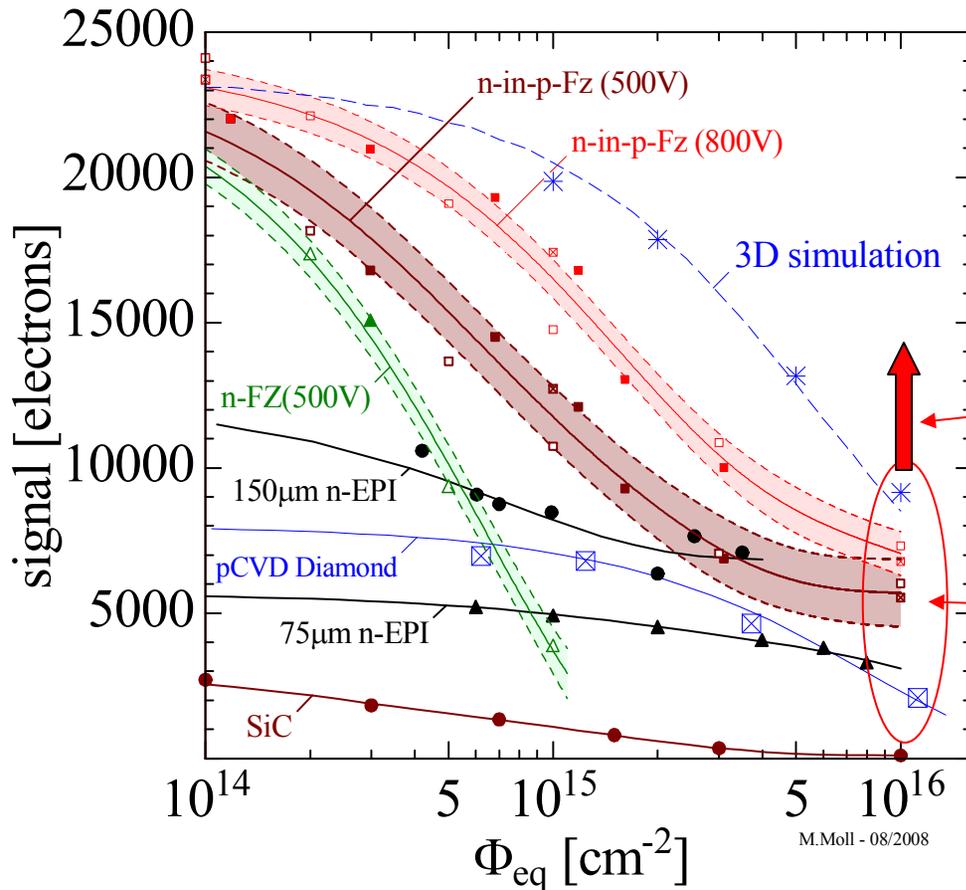
- [1] p/n-FZ, 300µm, (-30°C, 25ns), strip [Casse 2008]
- [2] p-FZ, 300µm, (-40°C, 25ns), strip [Mandic 2008]
- [3] n-SiC, 55µm, (2µs), pad [Moscatelli 2006]
- [4] pCVD Diamond, scaled to 500µm, 23 GeV p, strip [Adam et al. 2006, RD42]
- Note: Fluence normalized with damage factor for Silicon (0.62)
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- [6] n-EPI, 75µm, (-30°C, 25ns), pad [Kramberger 2006]
- [7] n-EPI, 150µm, (-30°C, 25ns), pad [Kramberger 2006]
- [8] n-EPI, 150µm, (-30°C, 25ns), strip [Messineo 2007]

highest fluence for strip detectors in LHC: The used p-in-n technology is sufficient

n-in-p technology should be sufficient for Super-LHC at radii presently (LHC) occupied by strip sensors

• Signal comparison for various Silicon sensors

Note: Measured partly under different conditions!
Lines to guide the eye (no modeling)!



- ### Silicon Sensors
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 - ▲ p-in-n (EPI), 75μm [6]
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 - n-in-p (FZ), 300μm, 800V, neutrons [1]
 - ▣ n-in-p (FZ), 300μm, 800V, 26MeV p [1]
 - ▲ p-in-n (FZ), 300μm, 500V, 23GeV p [1]
 - △ p-in-n (FZ), 300μm, 500V, neutrons [1]
 - * Double-sided 3D, 250 μm, simulation! [5]

- ### Other materials
- SiC, n-type, 55 μm, 900V, neutrons [3]
 - ▣ Diamond (pCVD), 500 μm [4] (RD42)

References:

- [1] p/n-FZ, 300μm, (-30°C, 25ns), strip [Casse 2008]
- [2] p-FZ, 300μm, (-40°C, 25ns), strip [Mandic 2008]
- [3] n-SiC, 55μm, (2μs), pad [Moscatelli 2006]
- [4] pCVD Diamond, scaled to 500μm, 23 GeV p, strip [Adam et al. 2006, RD42]
Note: Fluence normalized with damage factor for Silicon (0.62)
- [5] 3D, double sided, 250μm columns, 300μm substrate [Pennicard 2007]
- [6] n-EPI, 75μm, (-30°C, 25ns), pad [Kramberger 2006]
- [7] n-EPI, 150μm, (-30°C, 25ns), pad [Kramberger 2006]
- [8] n-EPI, 150μm, (-30°C, 25ns), strip [Messineo 2007]

Higher Voltage leads to charge multiplication

Beware: Signal shown and not S/N !

- All sensors suffer from radiation damage
- Presently three options for innermost pixel layers under investigation:
 - 3-D silicon sensors (decoupling drift distance from active depth)
 - Diamond sensors
 - Silicon planar sensors



Ongoing Work / Open Questions

- Performance of MCZ silicon in mixed fields -



- **Is MCZ silicon (n- and p-type) an option for SLHC detectors?**

- Protons induce predominantly defects that are positively charged
- Neutrons induce predominantly defects that are negatively charged
- Mixed Fields: Compensation?

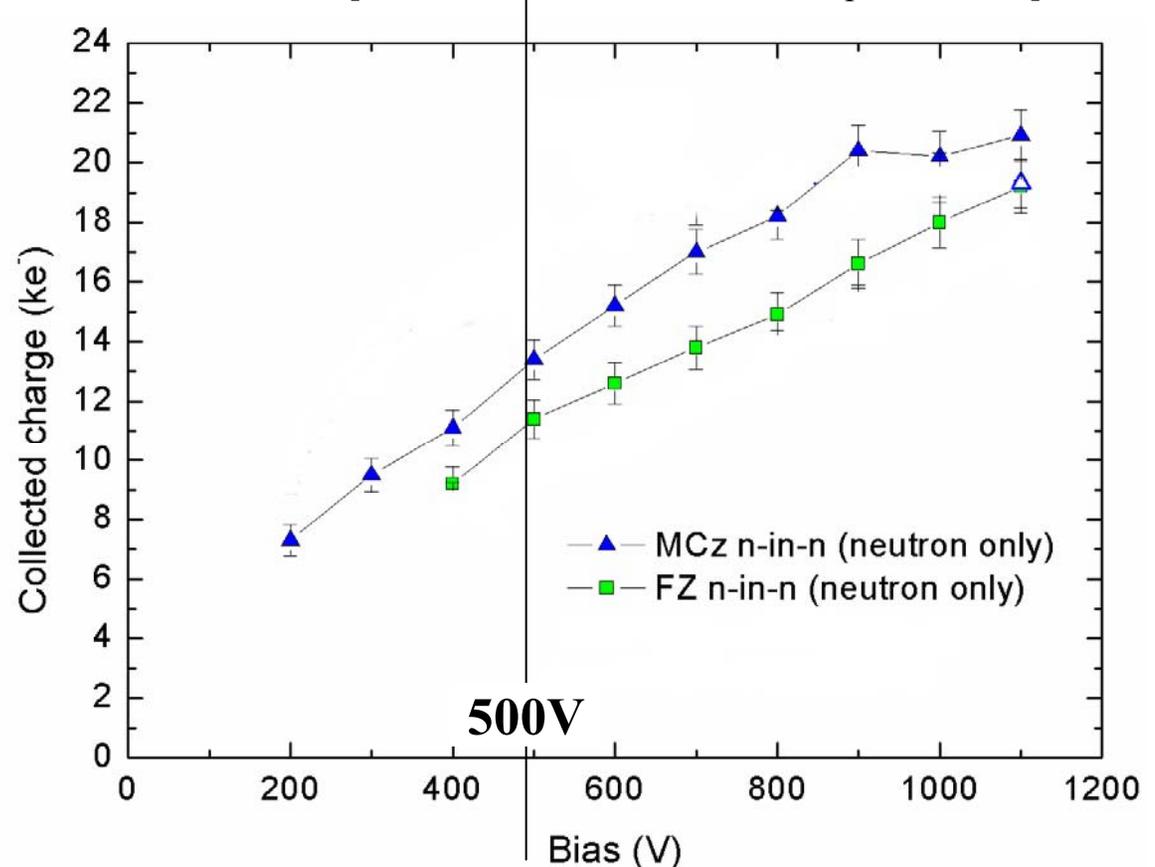
- **Mixed irradiations:**

- (a) $\Phi_{eq} = 5 \times 10^{14}$ neutrons
- (b) $\Phi_{eq} = 5 \times 10^{14}$ protons

- **FZ (n-in-n)**

- **MCZ (n-in-n)**

[T.Affolder et al. RD50 Workshop, Nov.2008]





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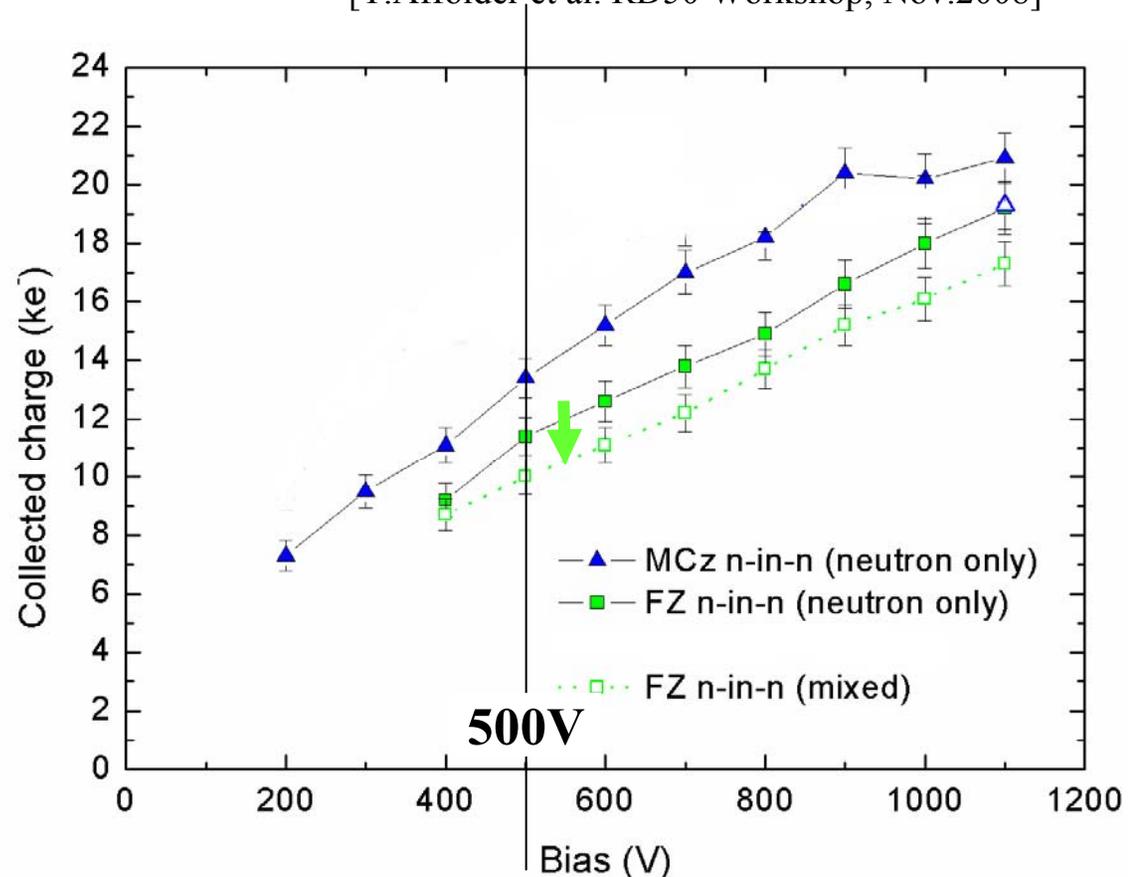
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Mixed Irradiation:

Damage additive!

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[T.Affolder et al. RD50 Workshop, Nov.2008]





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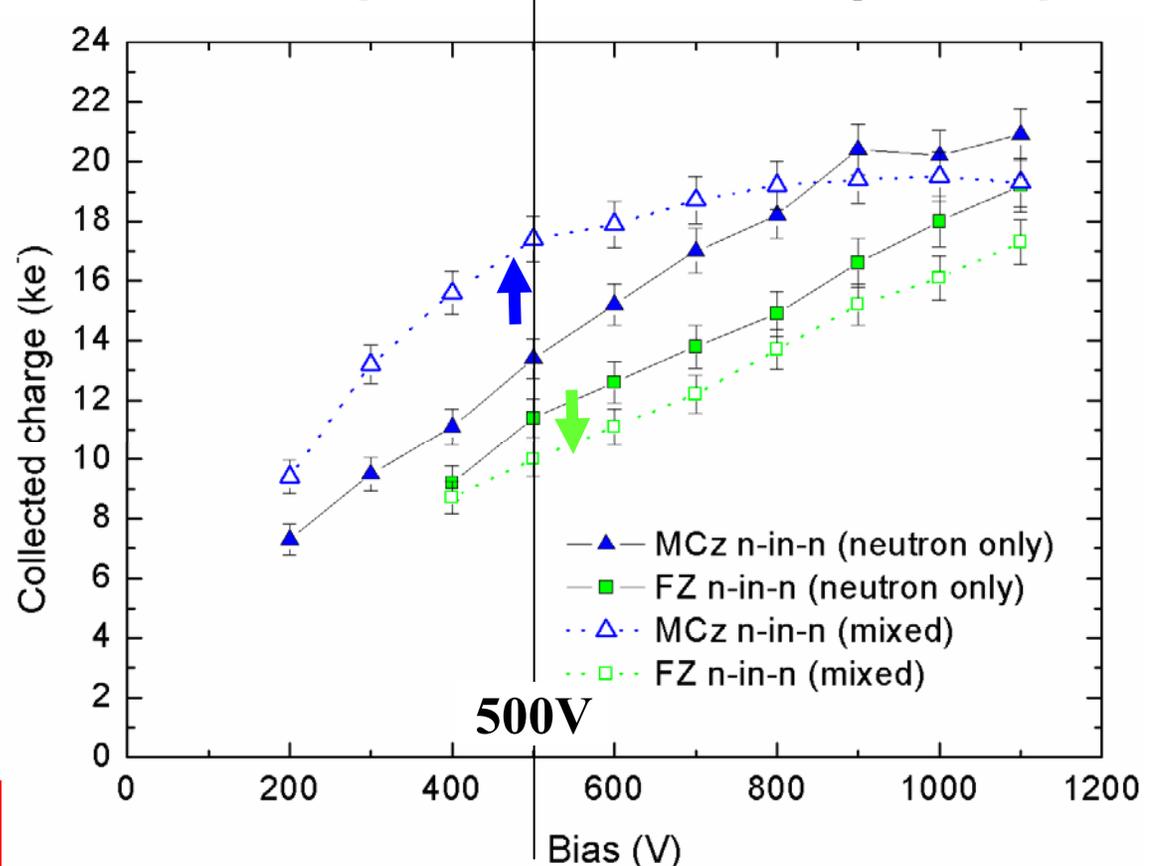
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- **MCZ (n-in-n)**

Mixed Irradiation:
Proton damage
“compensates” part of
neutron damage (N_{eff})

More charge collected at 500V after additional irradiation!!!

[T.Affolder et al. RD50 Workshop, Nov.2008]





Summary – Radiation Damage



- **Radiation Damage in Silicon Detectors**

- Change of **Depletion Voltage** (internal electric field, “type inversion”, reverse annealing, ...) (can be influenced by defect engineering!)
- Increase of **Leakage Current** (same for all silicon materials)
- Increase of **Charge Trapping** (same for all silicon materials)

Signal to Noise ratio is quantity to watch (material + geometry + electronics)

- **Microscopic defects & Defect Engineering**

- Good understanding of damage after γ -irradiation (point defects)
- Defects after hadron damage still to be better understood (cluster defects) although enormous progress in last 5 years a big question remains:
Which are the defects responsible for the charge trapping?

- **Approaches to obtain radiation tolerant devices:**

- **Material Engineering:** explore and develop new silicon materials
- **Device Engineering:** 3D, thin sensors, n-in-p, n-in-n, ...

⇒ **To obtain ultra radiation hard sensors a combination of material and device engineering approaches depending on radiation environment, application and available readout electronics will be best solution**



Summary – Detectors for SLHC



- **At fluences up to 10^{15}cm^{-2} (outer layers of SLHC detector):**

The change of the depletion voltage and the large area to be covered by detectors are major problems.

- **MCZ silicon detectors:** n-MCZ show good performance in mixed fields due to compensation of charged hadron damage and neutron damage (N_{eff} compensation) (more work needed)
- **p-type silicon microstrip detectors show very encouraging results:**

CCE ≈ 6500 e; $\Phi_{\text{eq}} = 4 \times 10^{15} \text{ cm}^{-2}$, $300\mu\text{m}$, immunity against reverse annealing!

This is presently the “most considered option” for the ATLAS SCT upgrade

- **At fluences $> 10^{15}\text{cm}^{-2}$ (Inner SLHC layers or innermost upgraded LHC pixel)**

The active thickness of any silicon material is significantly reduced due to trapping.

Collection of electrons at electrodes essential: Use n-in-p or n-in-n detectors!

- **Recent results show that planar silicon sensors might still give sufficient signal,**
(still some interest in epitaxial silicon and thin sensor options)
- **3D detectors** : looks promising, drawback: technology has to be optimized!
Many collaborations and sensor producers working on this.
- **Diamond** has become an interesting option (*Higher damage due to low energy protons?*)

- **Questions to be answered:**

- **a) Can we profit from the avalanche effects and control them ?**
- **b) Can we profit from MCZ (mixed field operation?)**





Acknowledgements



- **Some material taken from the following summary talks:**
 - *RD50 presentations on conferences: <http://www.cern.ch/rd50/>*
 - *Nigel Hessey: Eiroforum RADHARD 2010 Workshop, Lisbon 16-18 March 2010 (Path to upgrade)*
 - *Anthony Affolder: Presentations on the RD50 Workshop in June 2009 (sATLAS fluence levels)*
 - *Frank Hartmann: Presentation at the VCI conference in February 2010 (Diamond results)*
 - *... most references to particular works given on slides.*

Further information about RD50 activities: <http://cern.ch/rd50/>

Further R&D: RD42, RD39, ATLAS & CMS detector upgrade meetings, ATLAS IBL

... or go to DESY bldg. 67b ...
.... where you will find the

Particle Physics & Detector Development Group

***.. and more expertise
in this research field than I can offer.***